

Atomic precision mirror coatings for gravitational wave detectors

Jorden De Bolle, Christophe Detavernier

Overview

- Who are we?
 - The CoCooN research group
 - Atomic layer deposition (ALD)
 - Thin film characterisation
- Mirror coatings in GW detectors
 - Making mirrors reflective
 - Mirror coatings and noise
- ALD as alternative deposition technique
 - Current state of the art
 - Why ALD?
 - Growth of Ta_2O_5
 - Growth of SiO_2
- Structural characterisation of mirror coatings
 - Why structure is important
 - Total scattering experiments
 - PDF of Ta_2O_5

Who are we?

The CoCooN research group

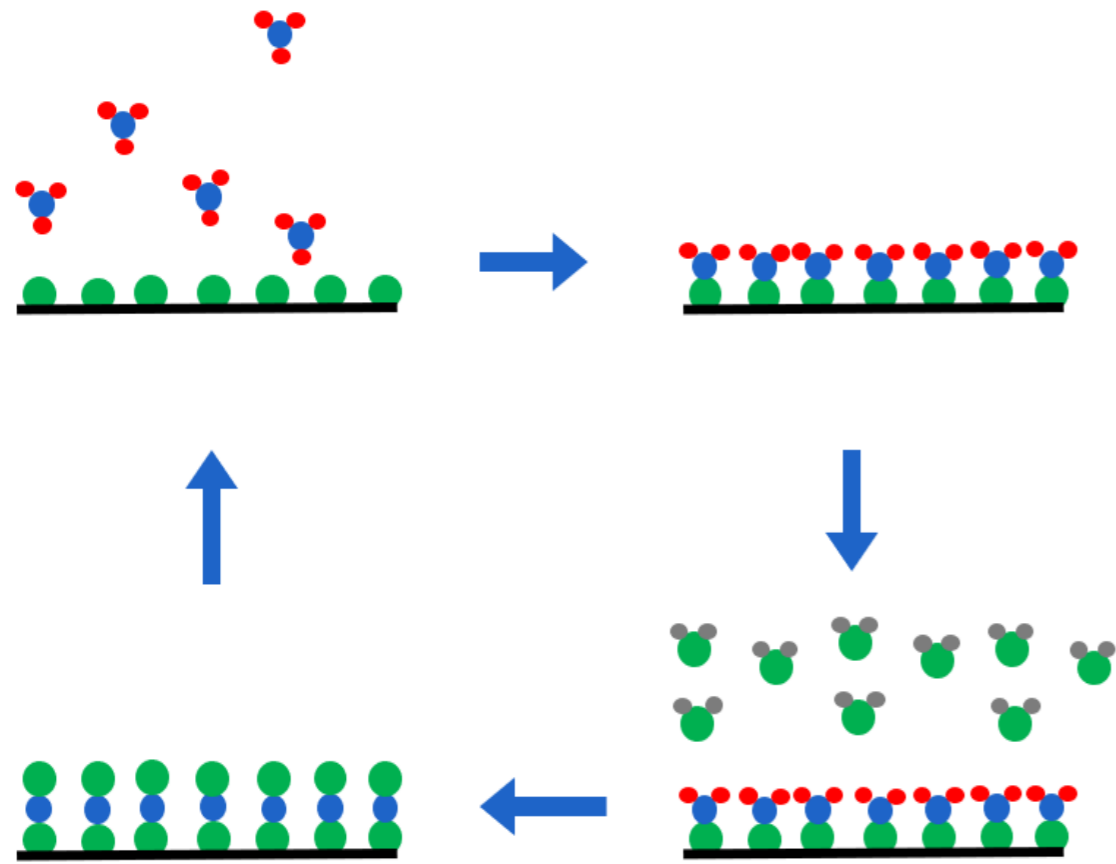


- Jorden De Bolle
- PhD student
- Physicist (MSc Physics, Ghent University)
- jorden.debolle@ugent.be

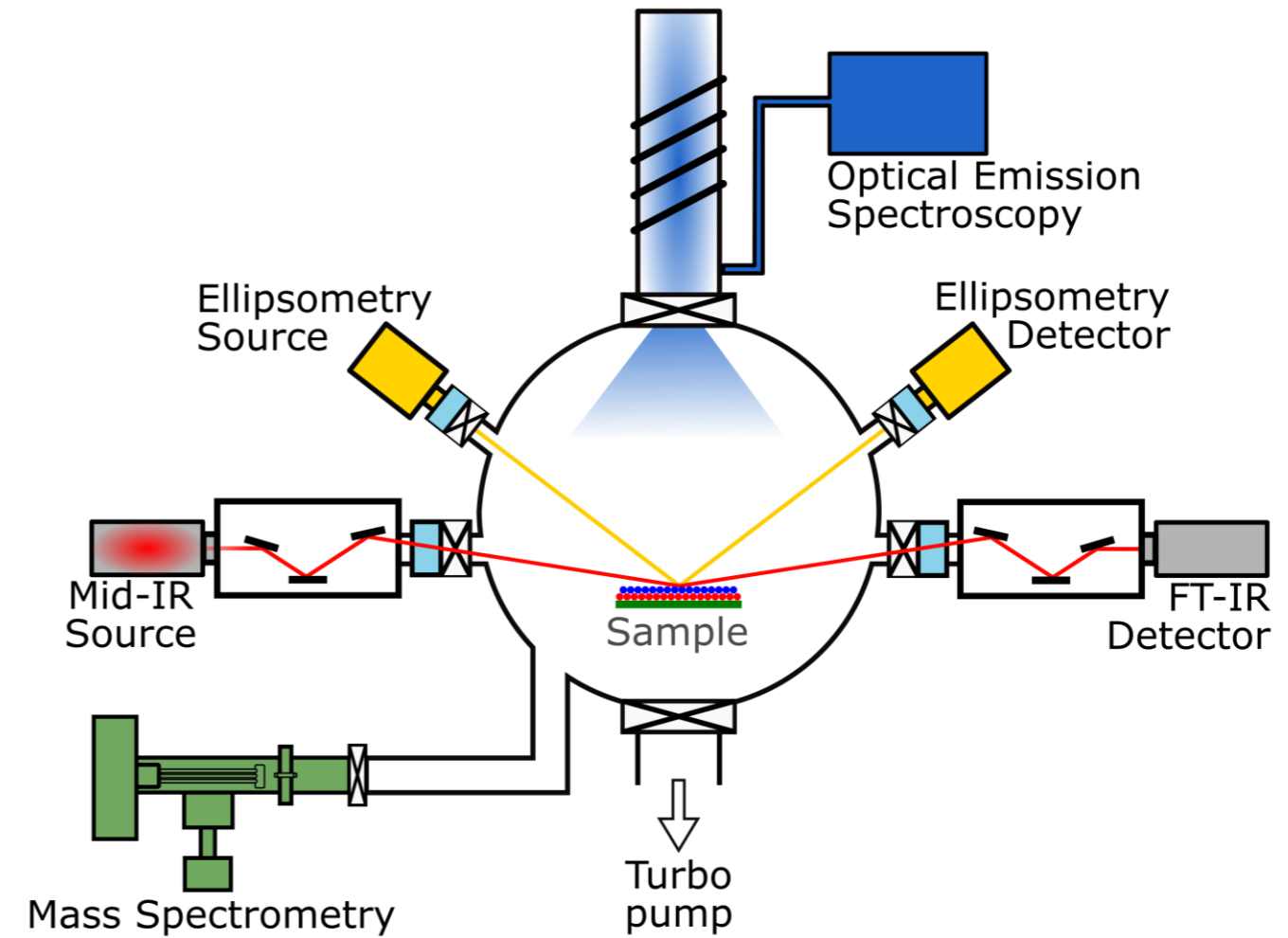


- CoCooN research group (Conformal Coating of Nanomaterials)
- Thin film and material research
- Application driven (batteries, proton conductors...) and fundamental research

Atomic layer deposition (ALD)



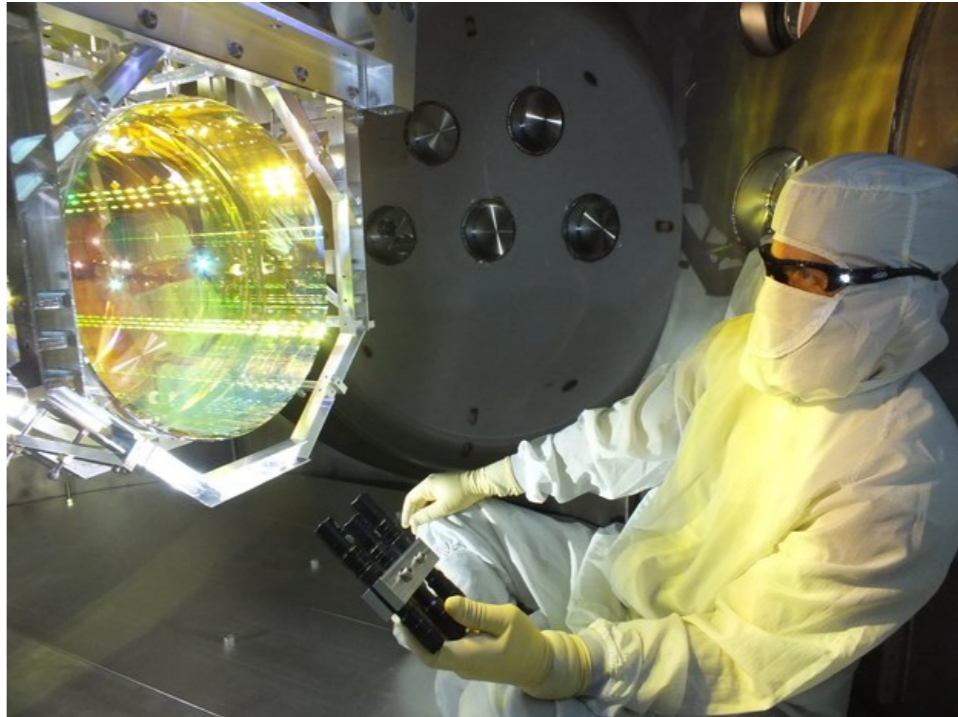
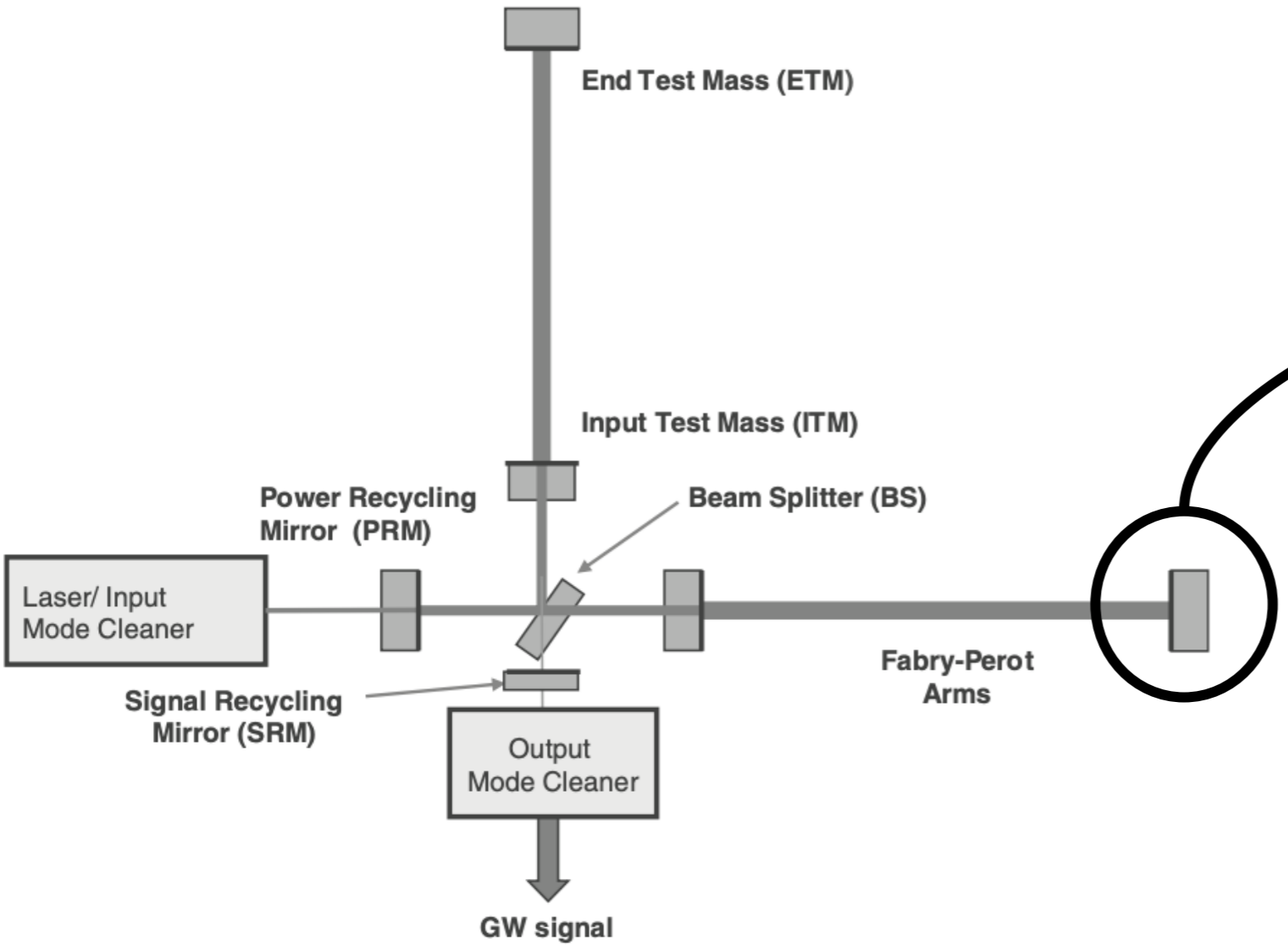
Self-limiting reactions between substrate and precursor gases!



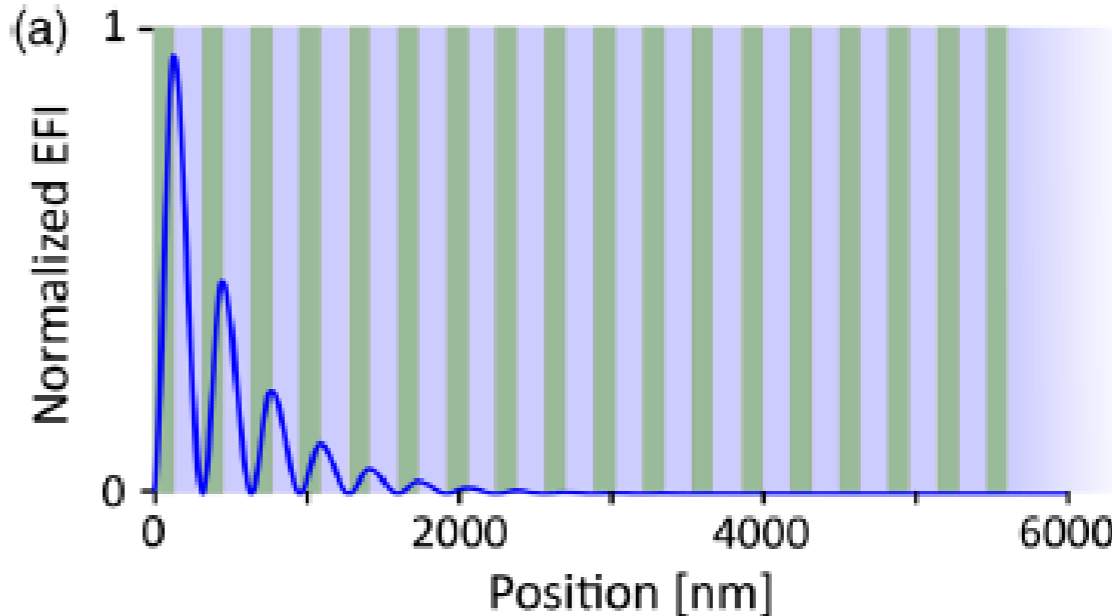
- 8 ALD reactors, 3 MLD reactors
- 1 mobile ALD reactor to take to a synchrotron facility
- PVD reactors
- Characterization:
 - Ellipsometry (in situ during ALD and anneal, ex situ)
 - FTIR (in situ during ALD, ex situ)
 - XRR (ex situ)
 - XRD (in situ during anneal, ex situ)
 - Stress measurements (in situ during anneal, ex situ)
 - Mass spectrometry (in situ during ALD)
 - XPS (in vacuo during ALD, ex situ)
 - SEM (ex situ)
 - ...
- Characterization at synchrotron facilities (GISAXS (in situ during ALD and anneal and ex situ), PDF...)

Mirror coatings in GW detectors

Making mirrors reflective

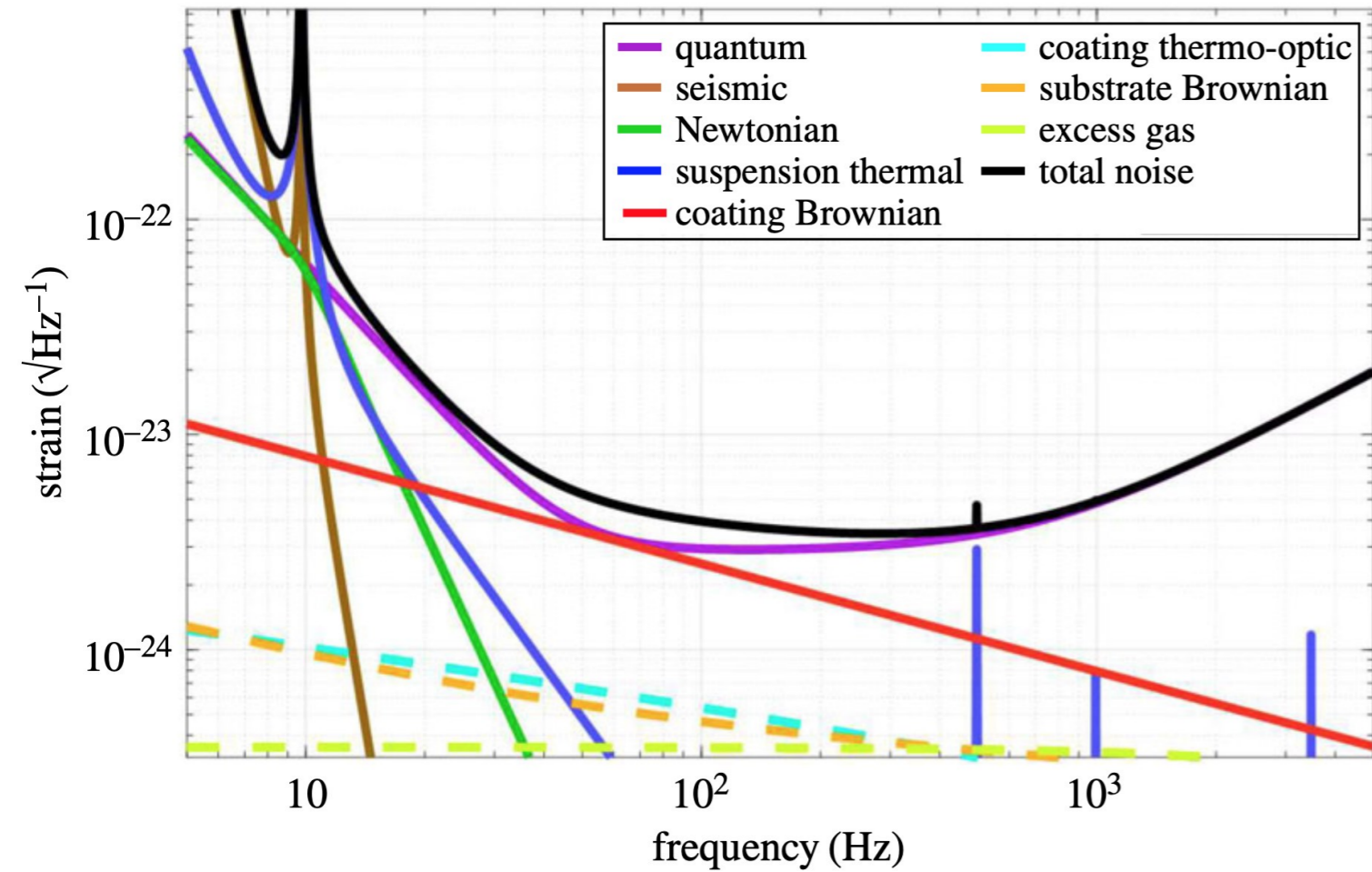


- Mirrors operate as Bragg reflectors
- Key components of the detectors



Mirror coatings and noise

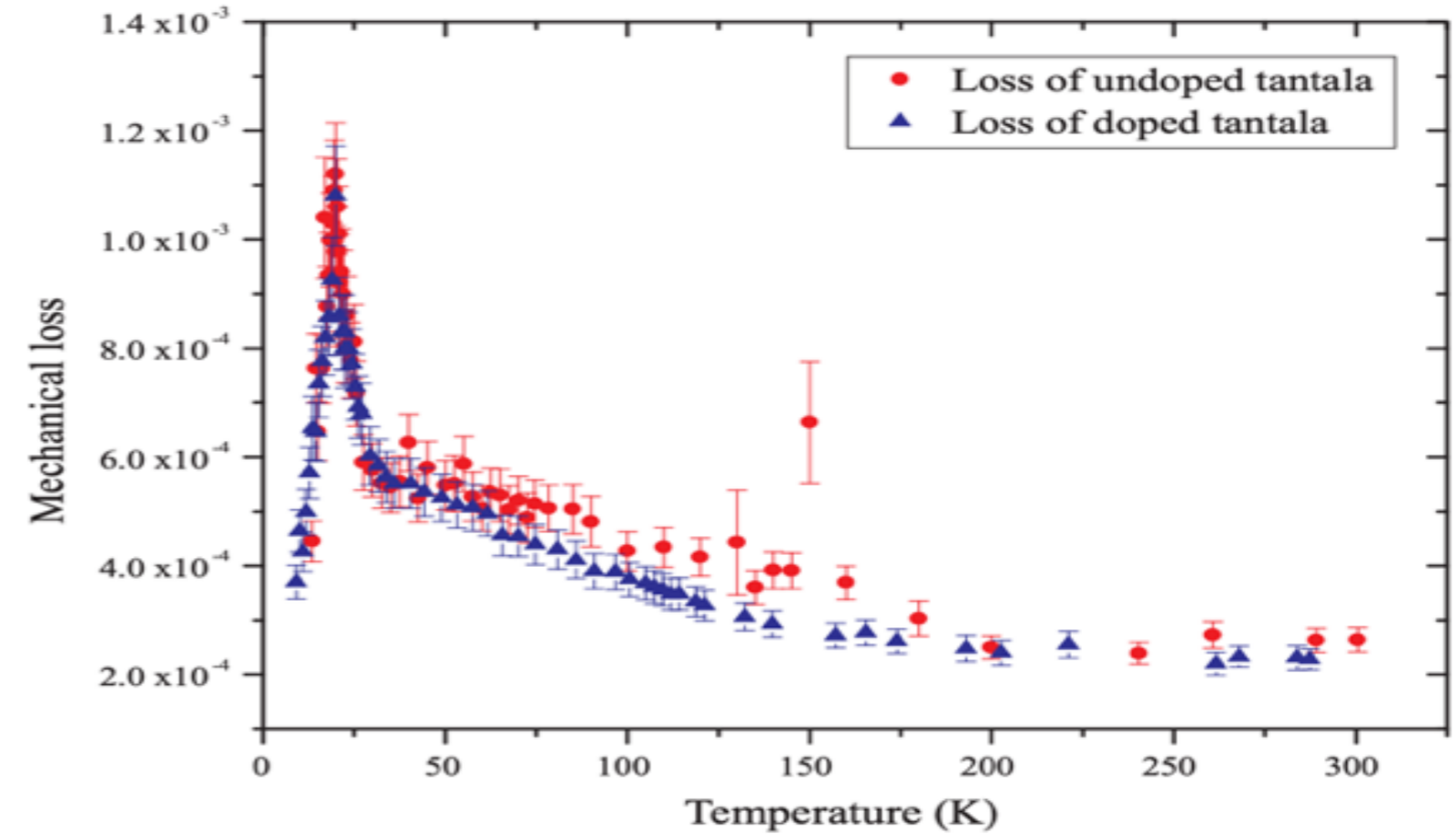
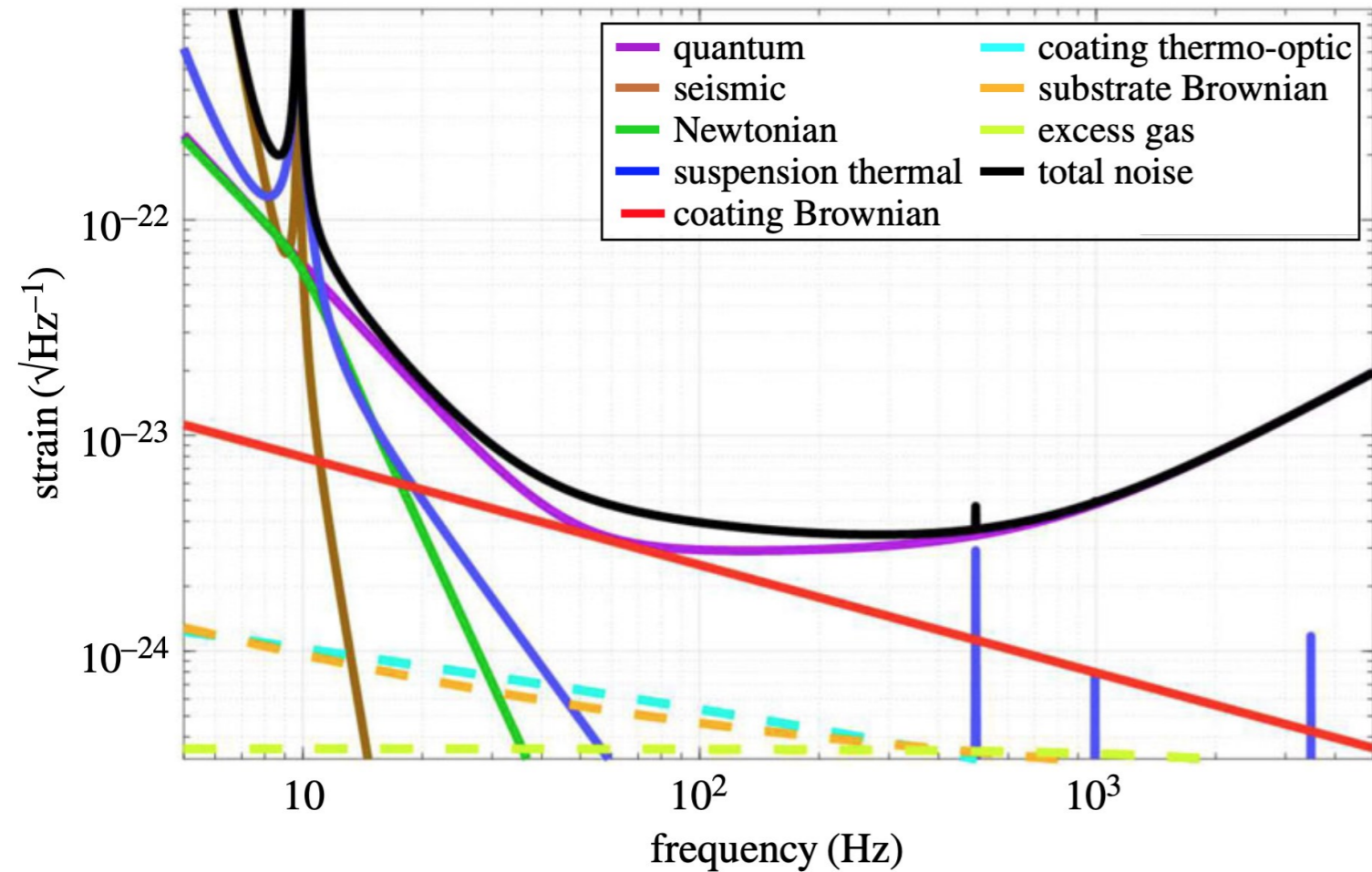
aLIGO noise curve: $P_{\text{in}} = 125.0 \text{ W}$



- Mirror coatings contribute large fraction to total detector noise

Mirror coatings and noise

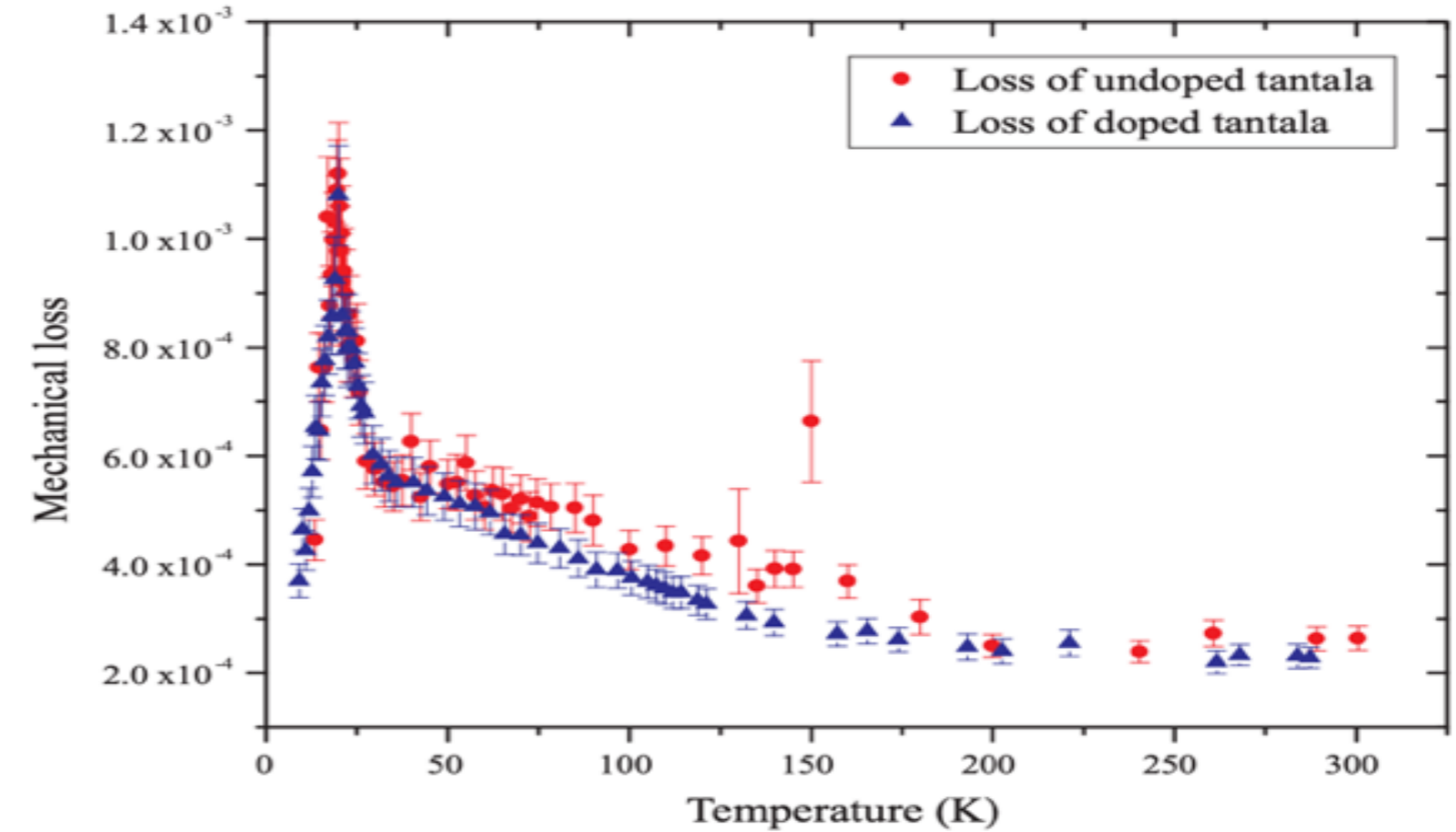
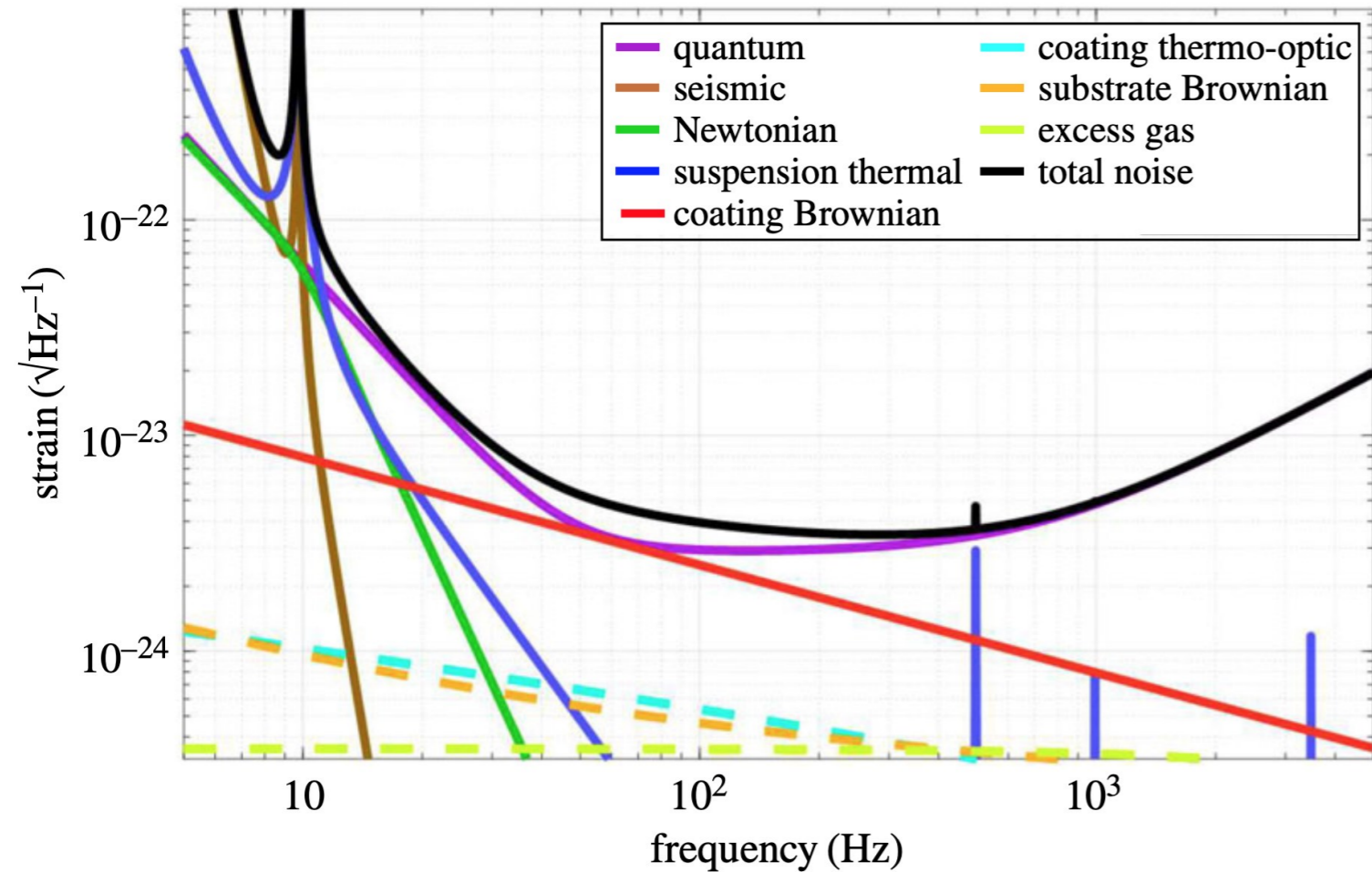
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- Mirror coatings contribute large fraction to total detector noise
- Current state of the art coatings not suited for operation in future detectors

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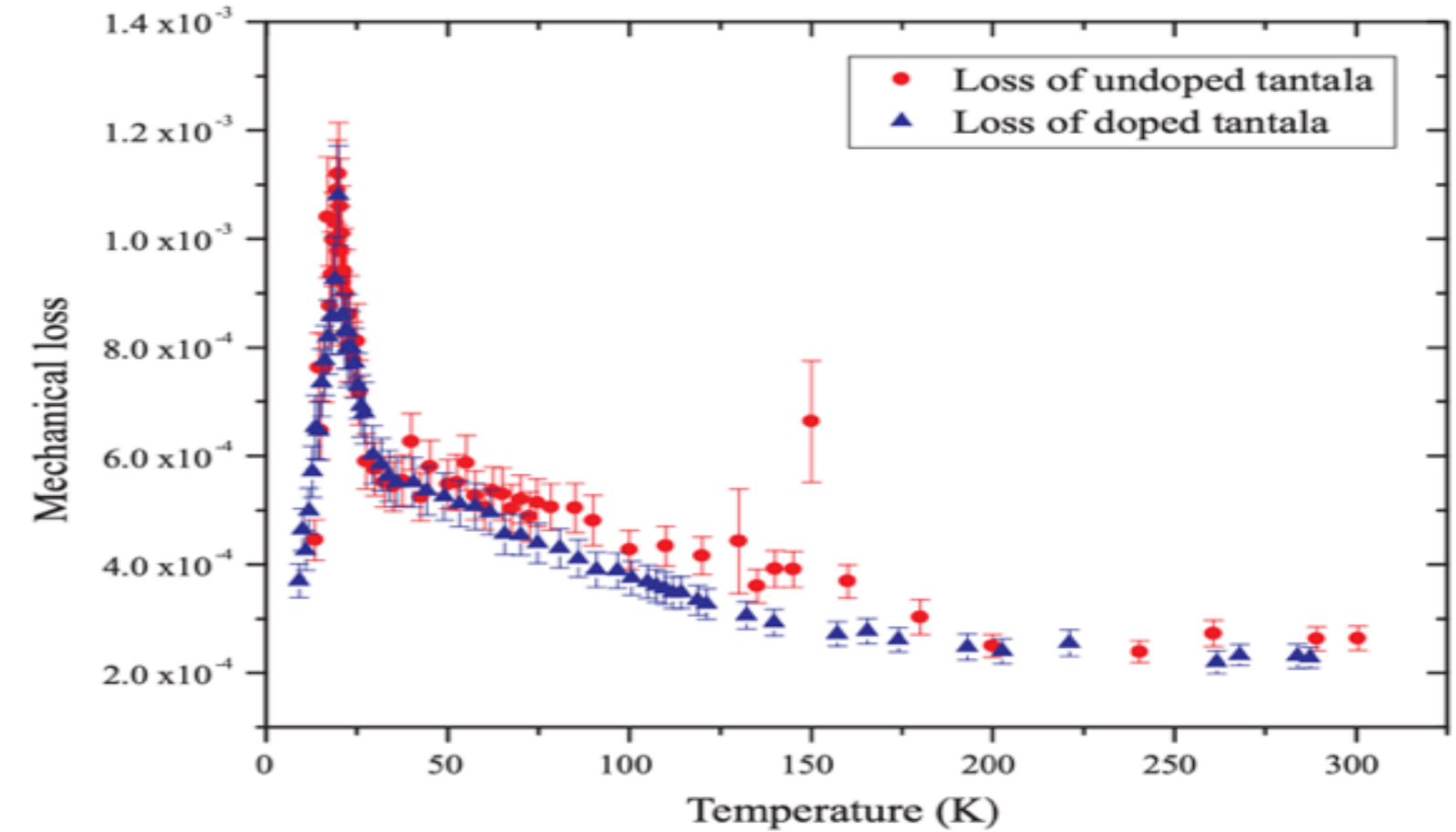
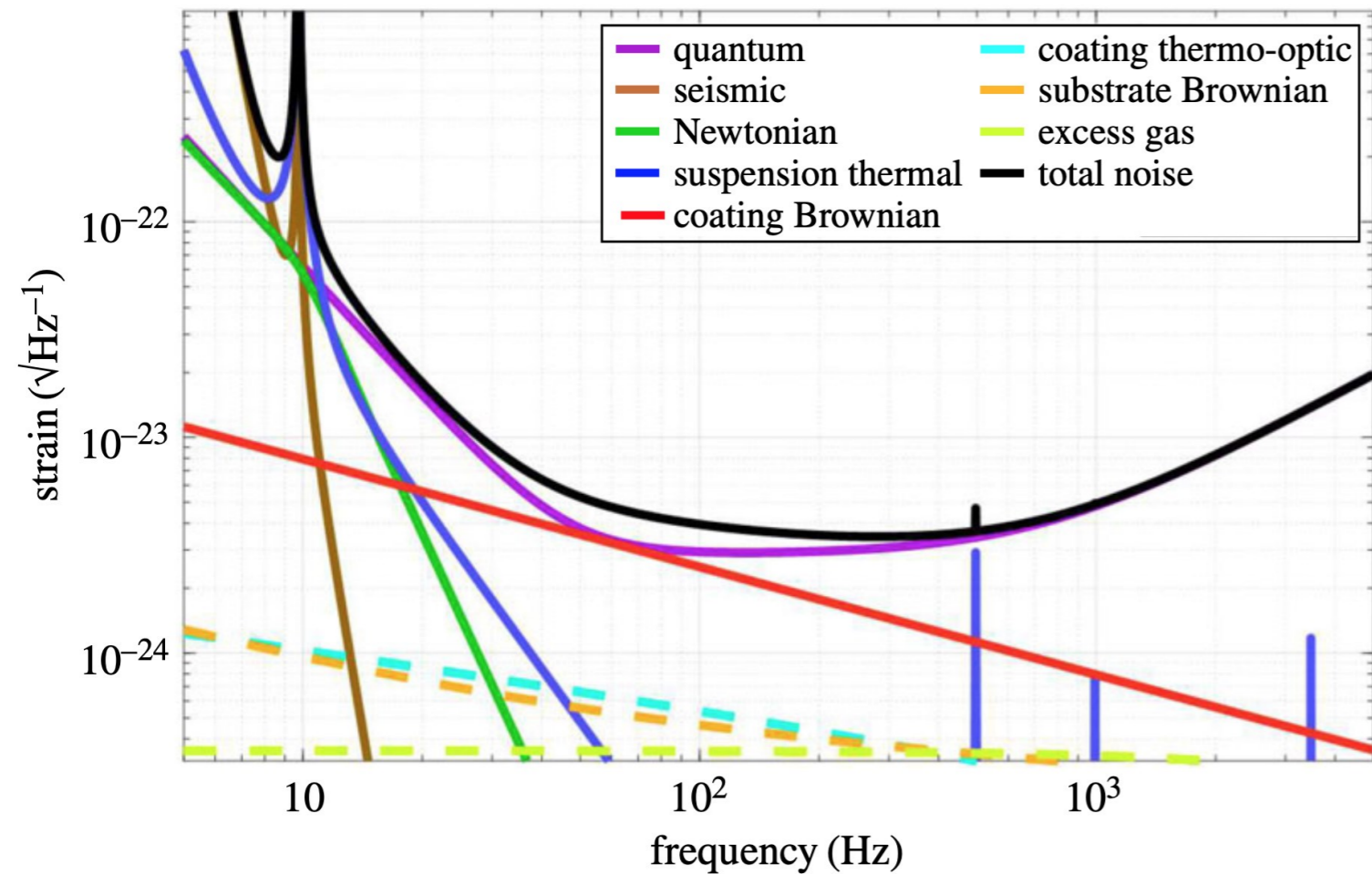
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- Need for new coating materials and coating designs

Mirror coatings and noise

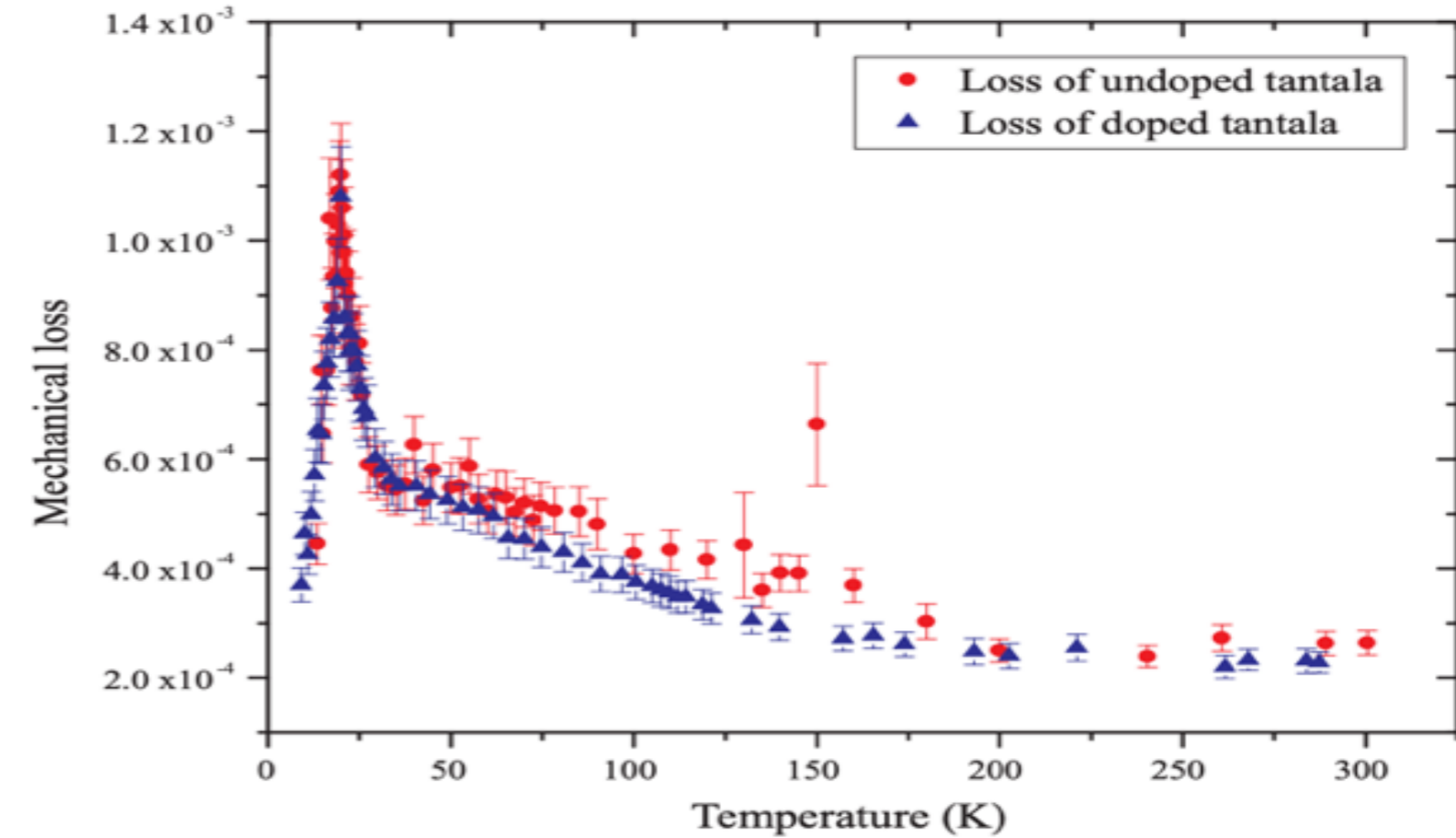
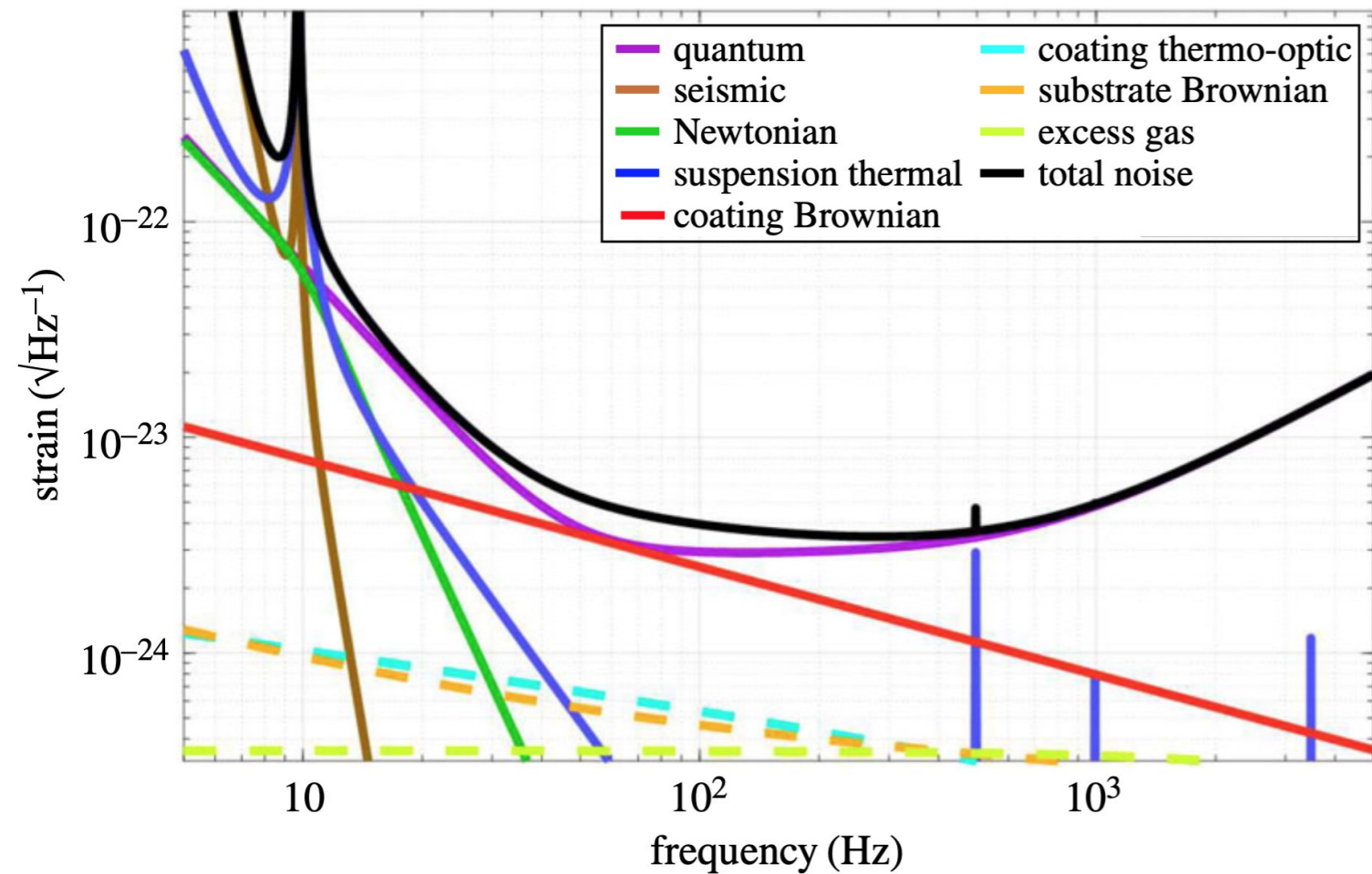
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- Need for more knowledge on how atomic structure influences performance and how this can be controlled

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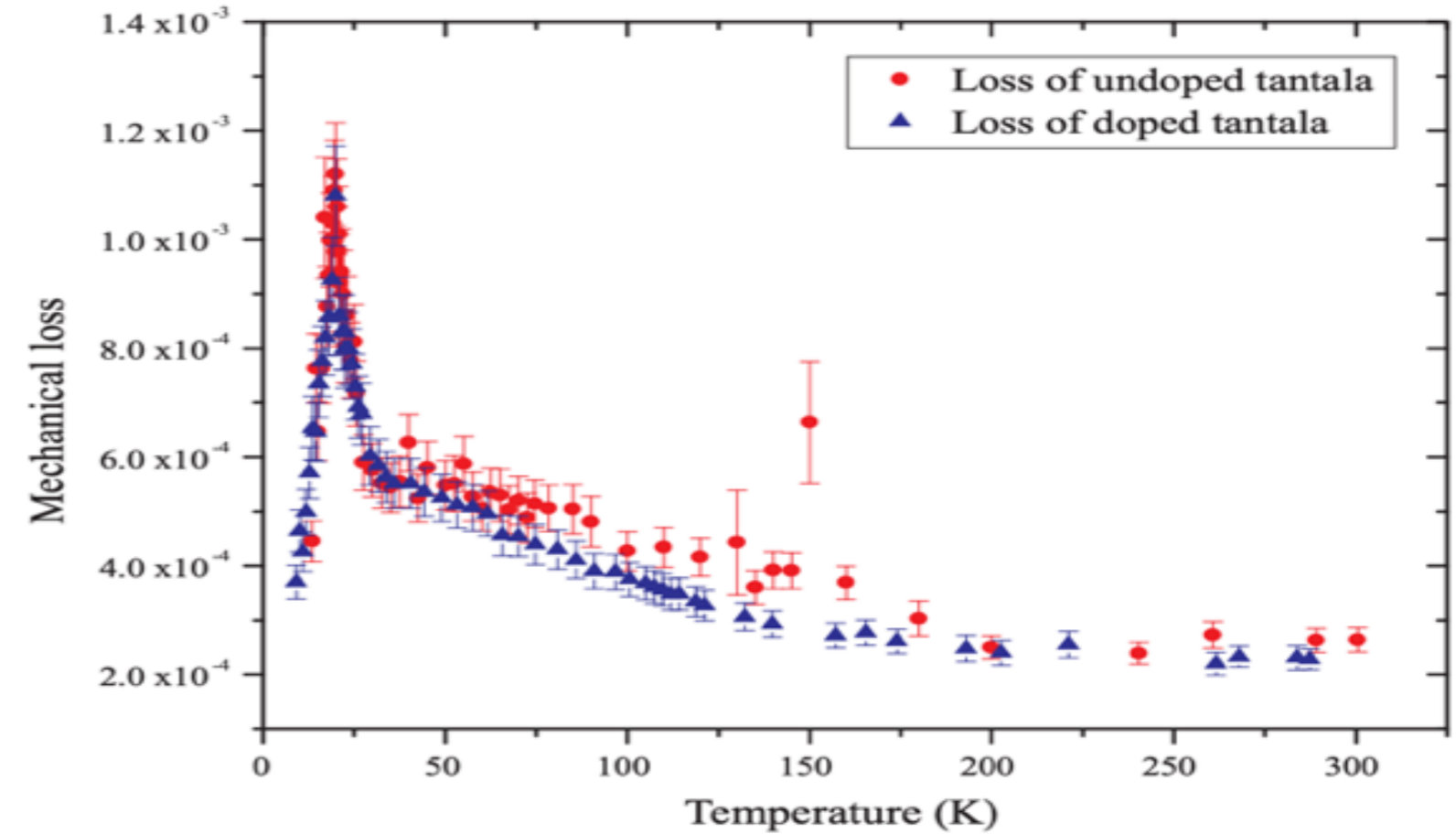
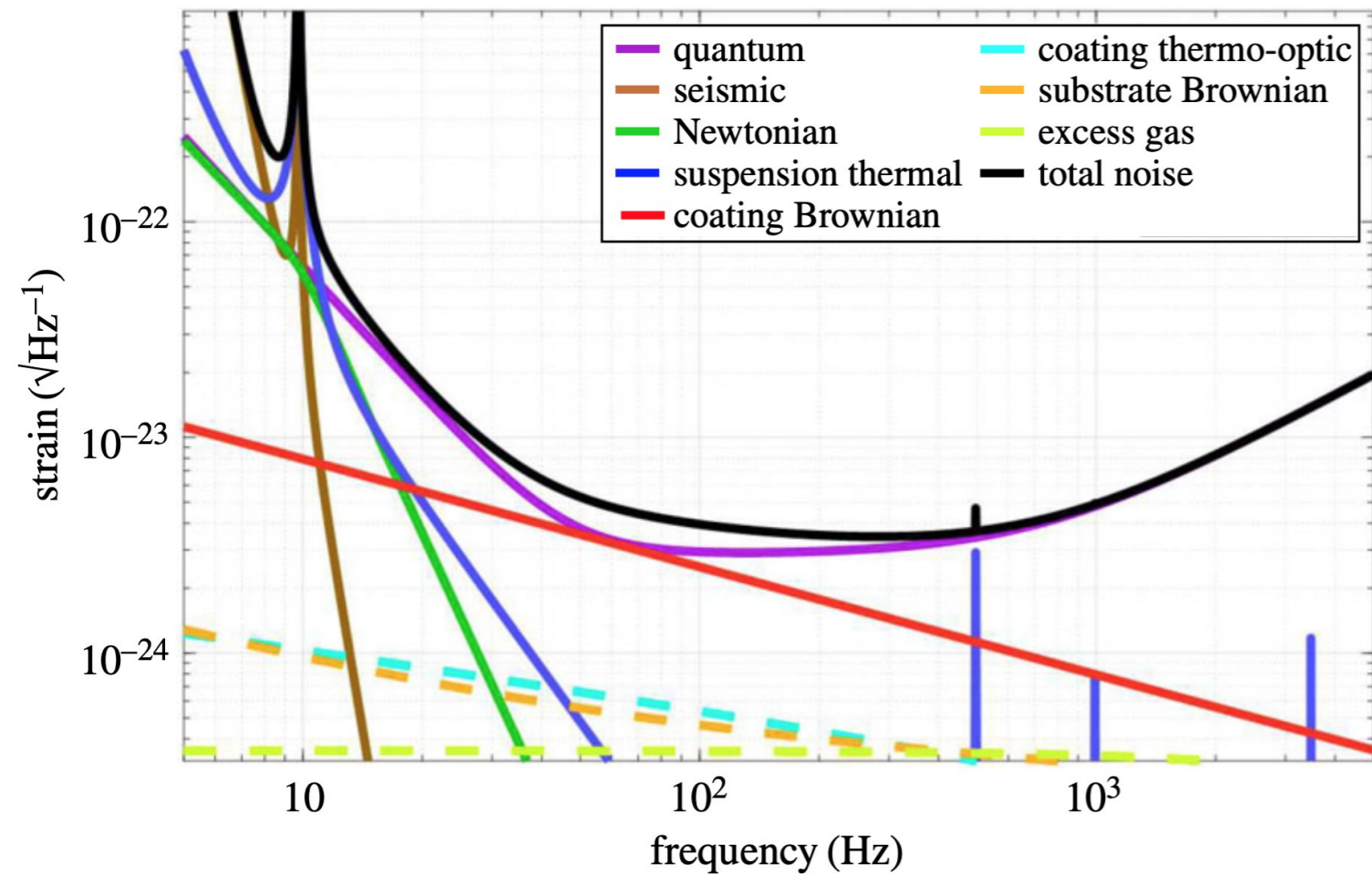
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Mirror coatings and noise

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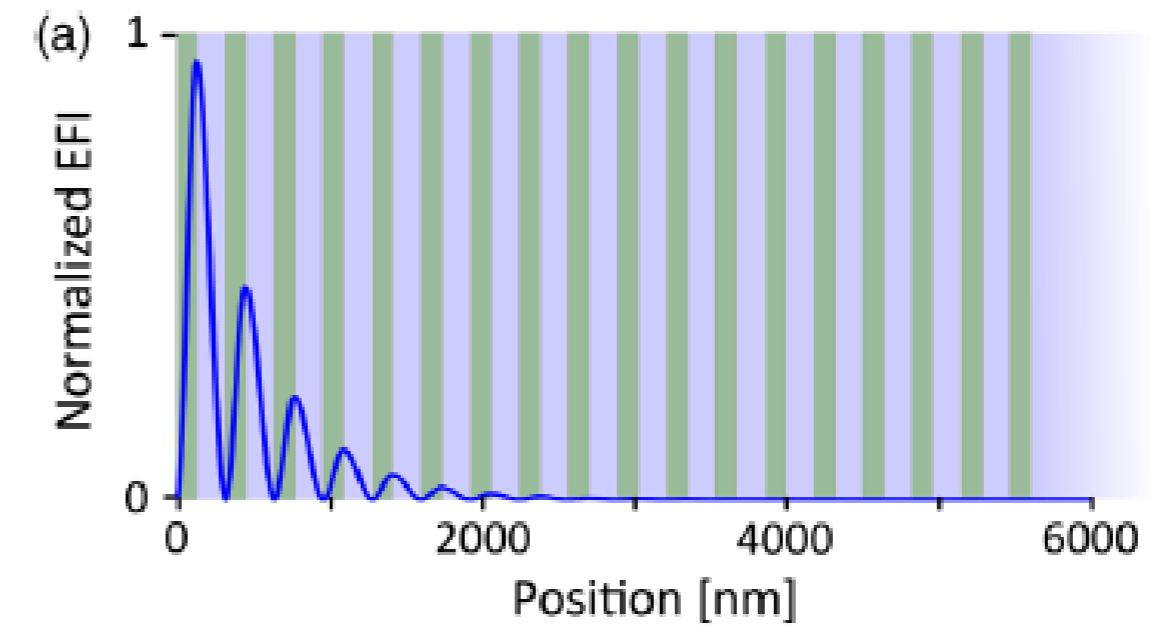
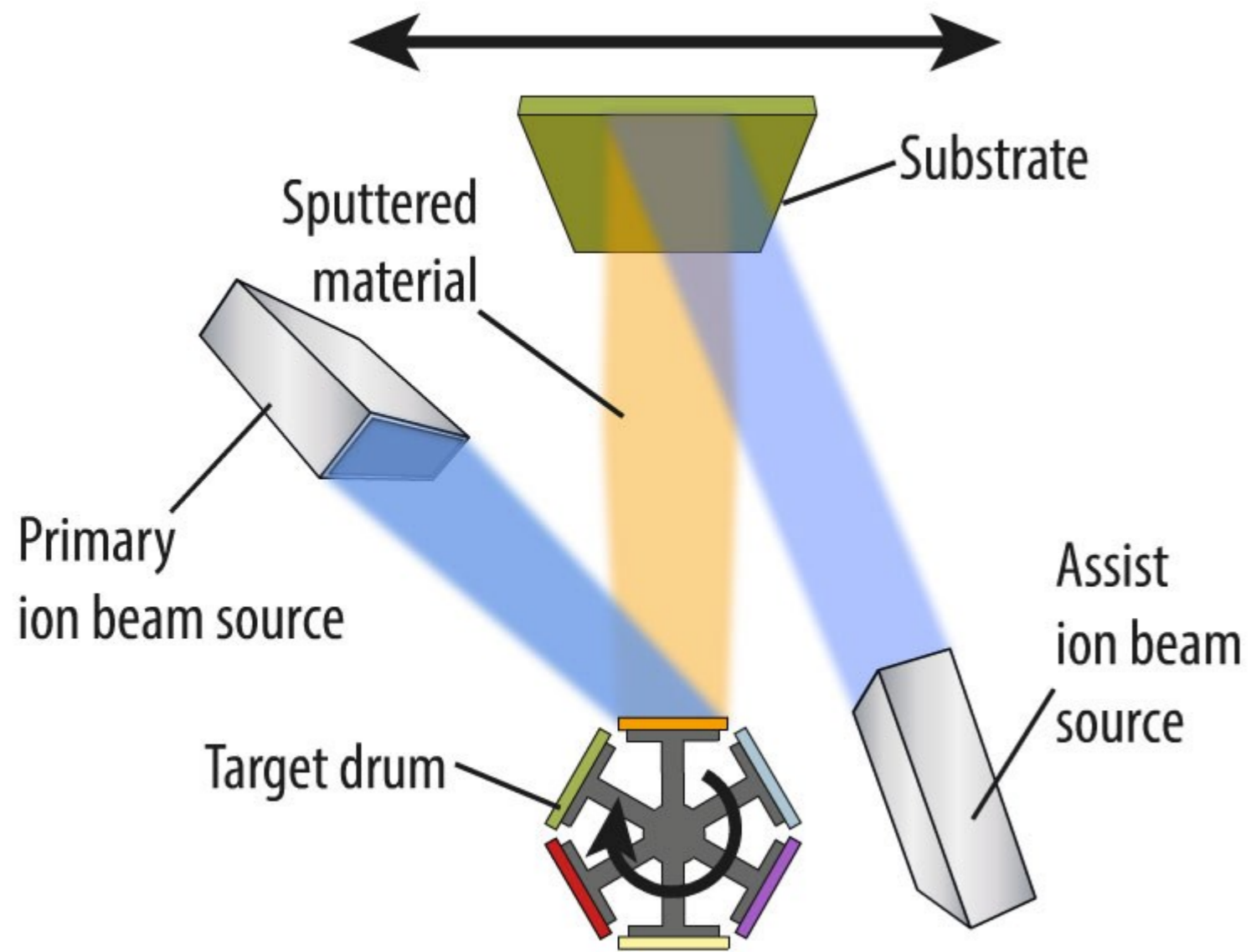


- Mirror coatings contribute large fraction to total detector noise
- Current state of the art coatings not suited for operation in future detectors
- Need for new coating materials and coating designs ← **ALD as alternative deposition technique**
- Need for more knowledge on how atomic structure influences performance and how this can be controlled ← **structural characterisation with total scattering measurements**

ALD as alternative deposition technique

Current state of the art

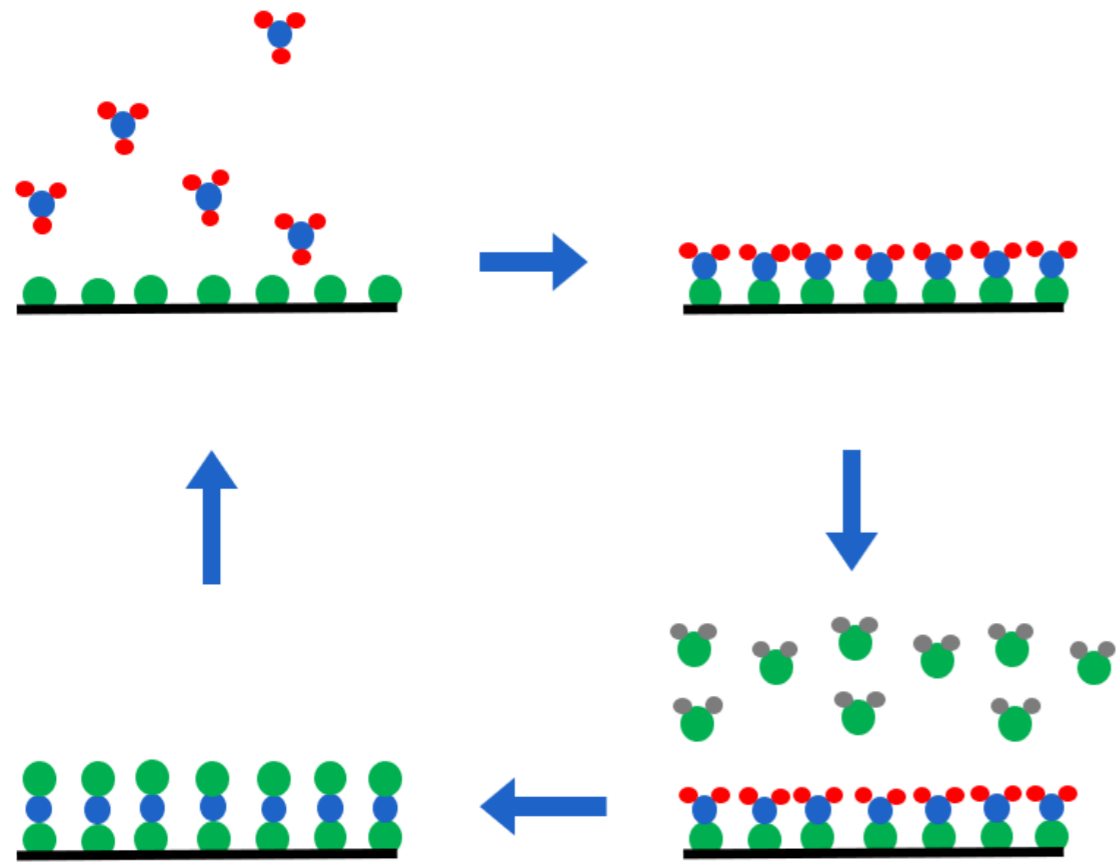
Ion beam sputtering is used to deposit coatings of Ti:Ta₂O₅ and SiO₂



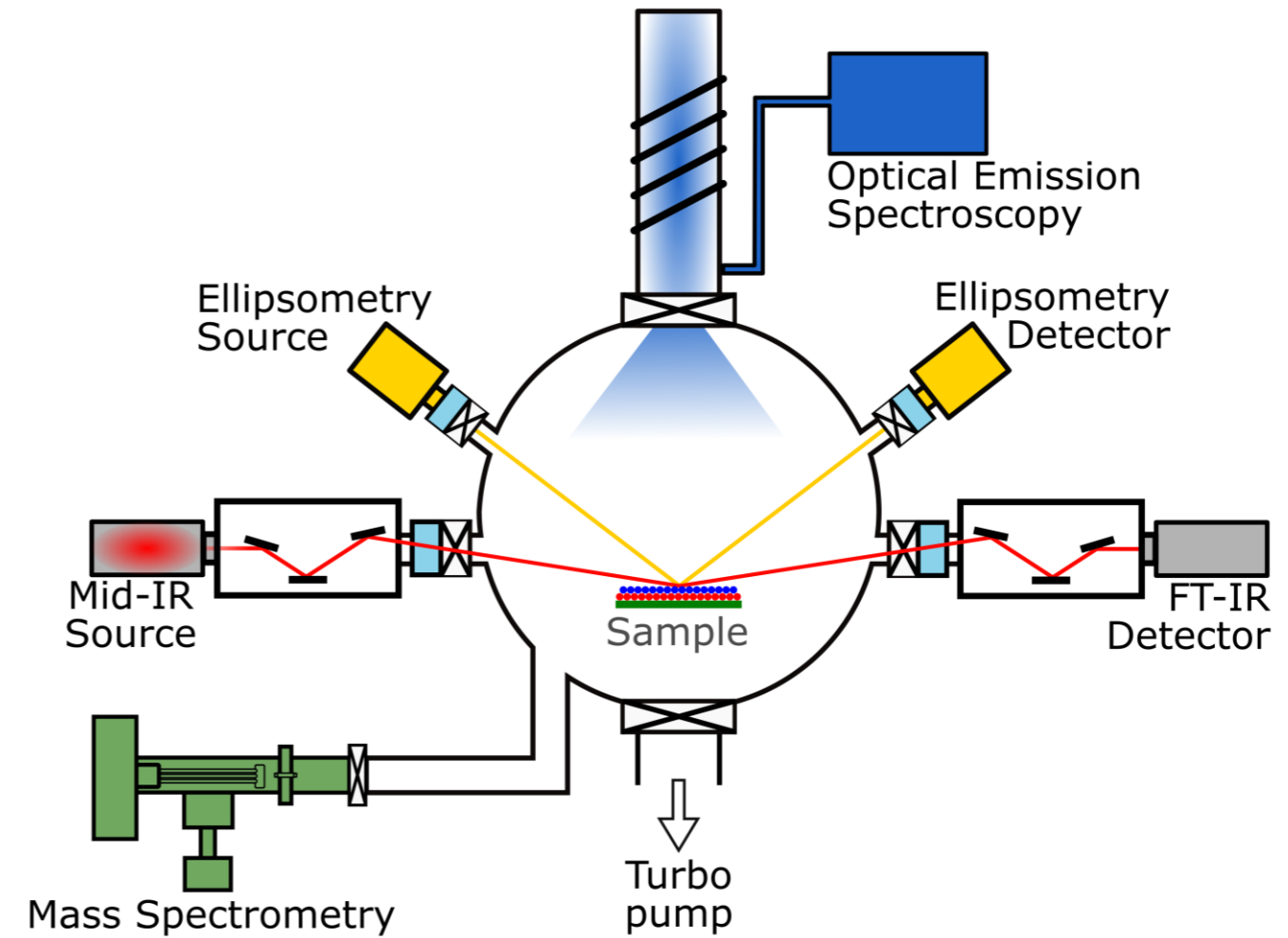
SiO₂ Ta₂O₅



Atomic layer deposition (ALD)



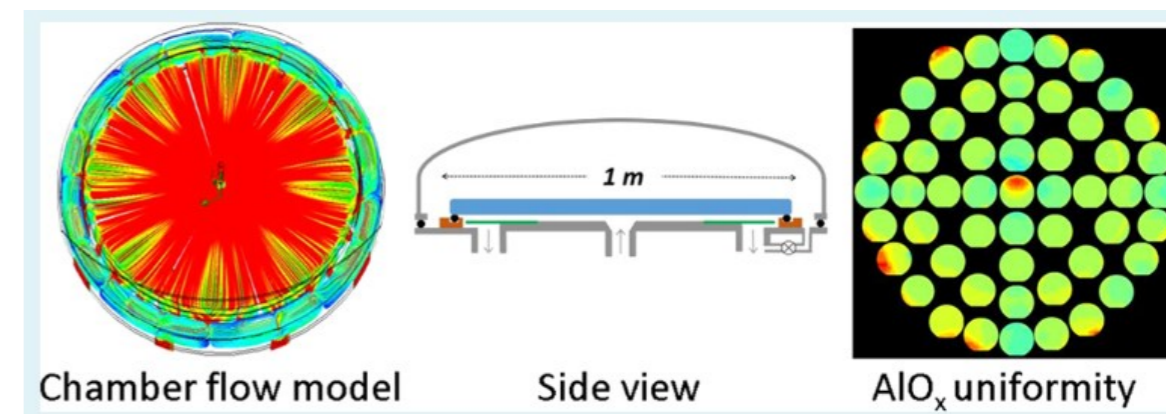
Self-limiting reactions between substrate and precursor gases!



Why ALD?

Scaling Atomic Layer Deposition to Astronomical Optic Sizes: Low-Temperature Aluminum Oxide in a Meter-Sized Chamber

David M. Fryauf,^{*,†} Andrew C. Phillips,[‡] Michael J. Bolte,[§] Aaron Feldman,^{||} Gary S. Tompa,^{||} and Nobuhiko P. Kobayashi[†]



Available ALD processes at CoCooN

(Click for selection and/or link to paper)

H																He	
Li	Be										B	C	N	O	F	Ne	
Na	Mg										Al	Si	P	S	Cl	Ar	
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe
Cs	Ba		Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
Fr	Ra		Rf	Db	Sg	Bh	Hs	Mt	Ds	Rg	Cn	Uut	Fl	Uup	Lv	Uus	Uuo

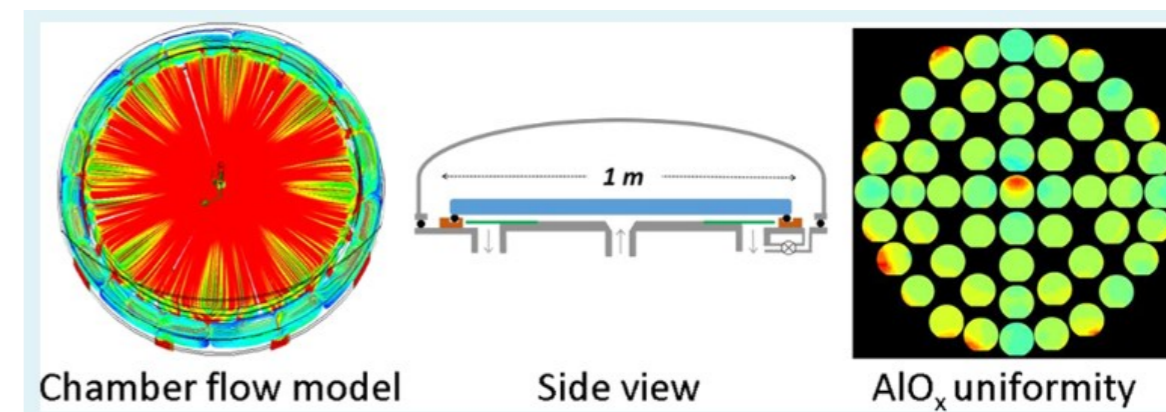
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- Silicate
- Phosphate
- Oxide
- Nitride
- MLD
- Metal

✓ Atomic thickness control

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Cs	Ba		Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
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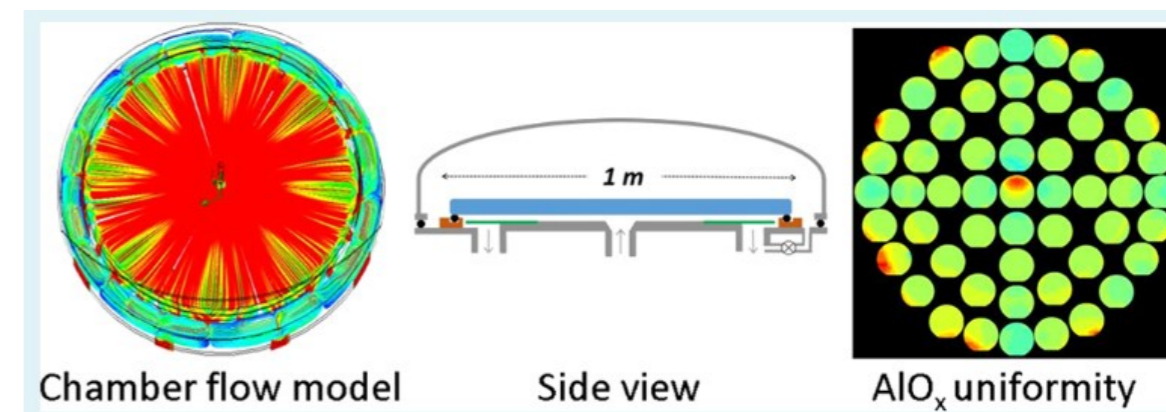
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- ✓ Atomic thickness control
- ✓ Superior uniformity

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Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe
Cs	Ba		Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
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Legend:

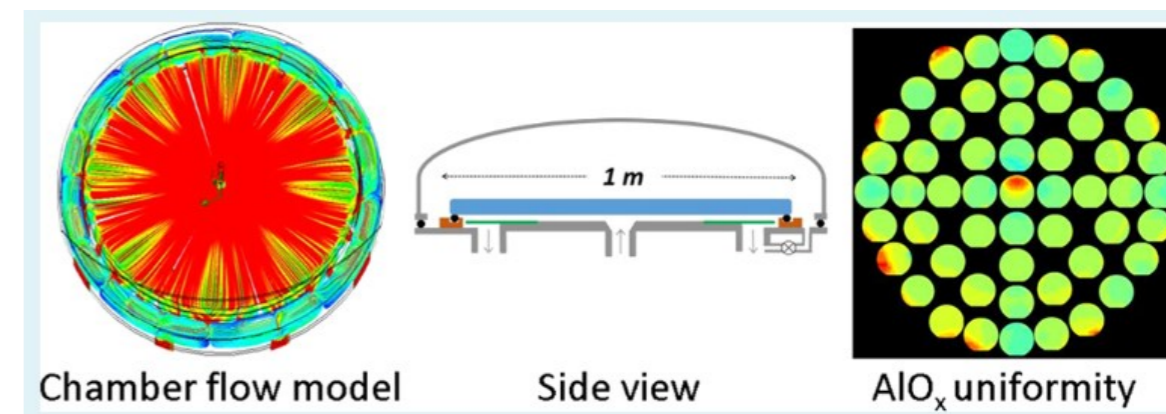
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- ✓ Atomic thickness control
- ✓ Superior uniformity
- ✓ Easily scaleable
- ✓ Wide variety of materials

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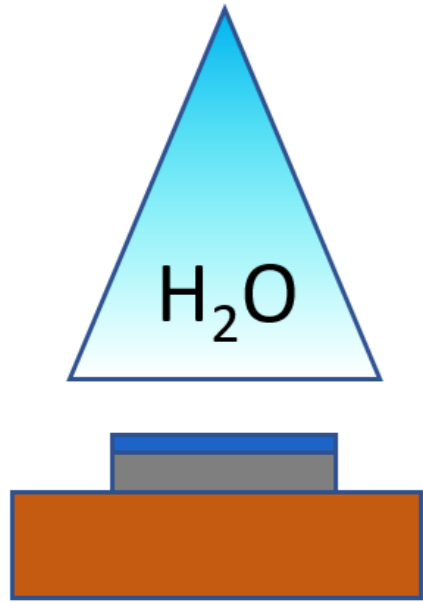
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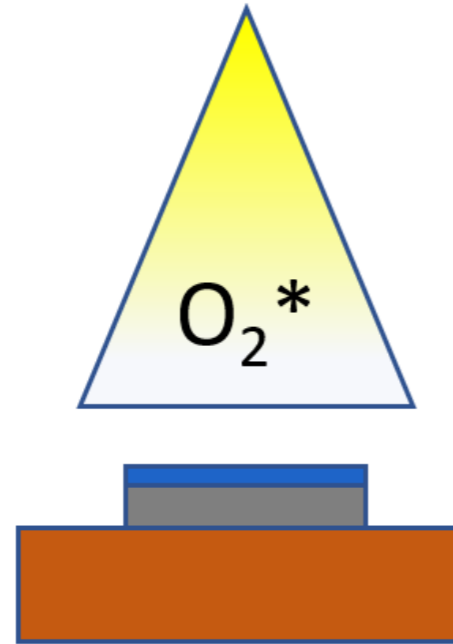
- ✓ Atomic thickness control
- ✓ Superior uniformity
- ✓ Easily scaleable
- ✓ Wide variety of materials
- ✗ Slow

Growth of Ta_2O_5

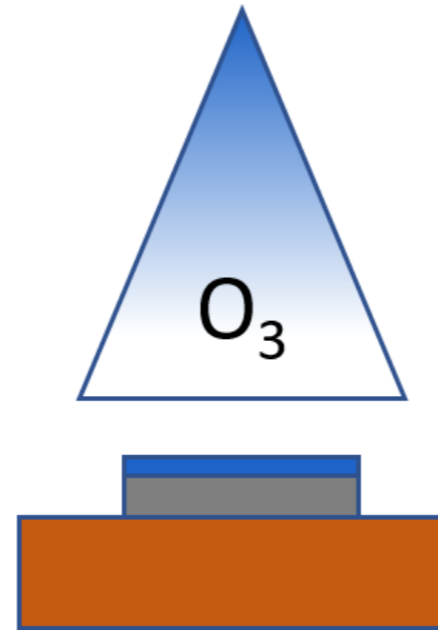
PDMAT/ H_2O



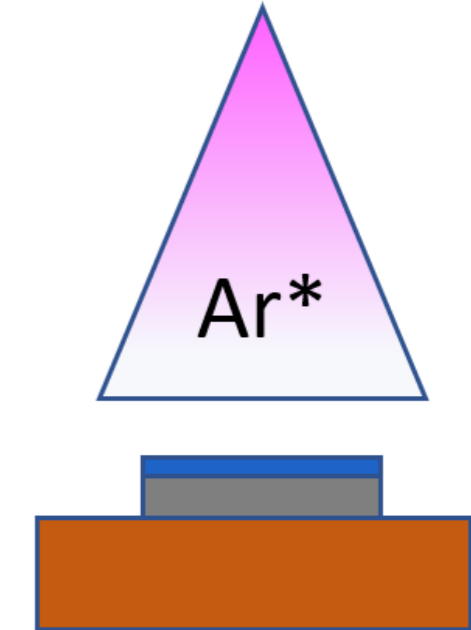
PDMAT/ O_2^*



PDMAT/ O_3



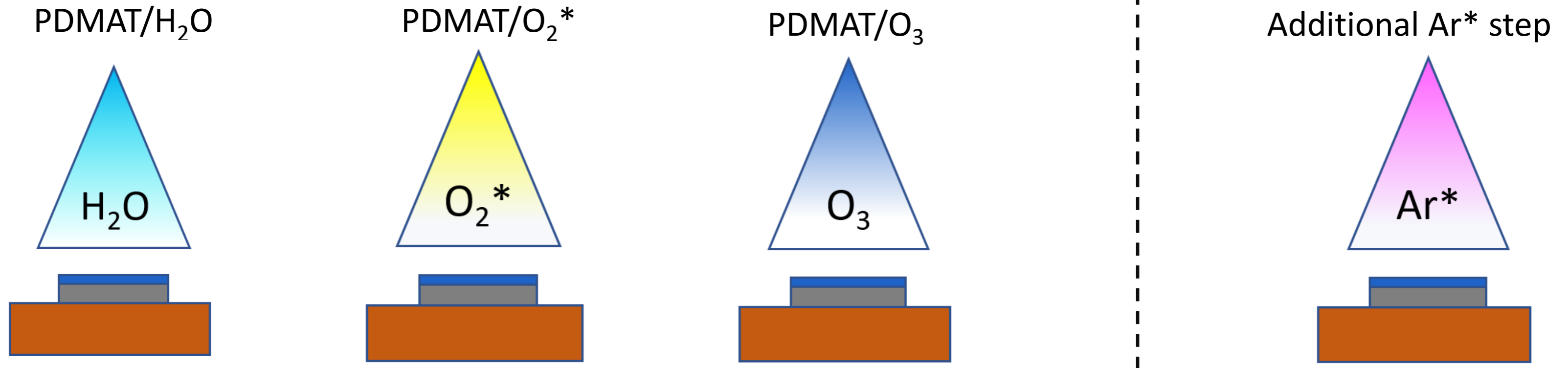
Additional Ar^* step



Influence of coreactant on:

- Growth speed
- Density
- Purity
- Optical absorption
- Mechanical losses

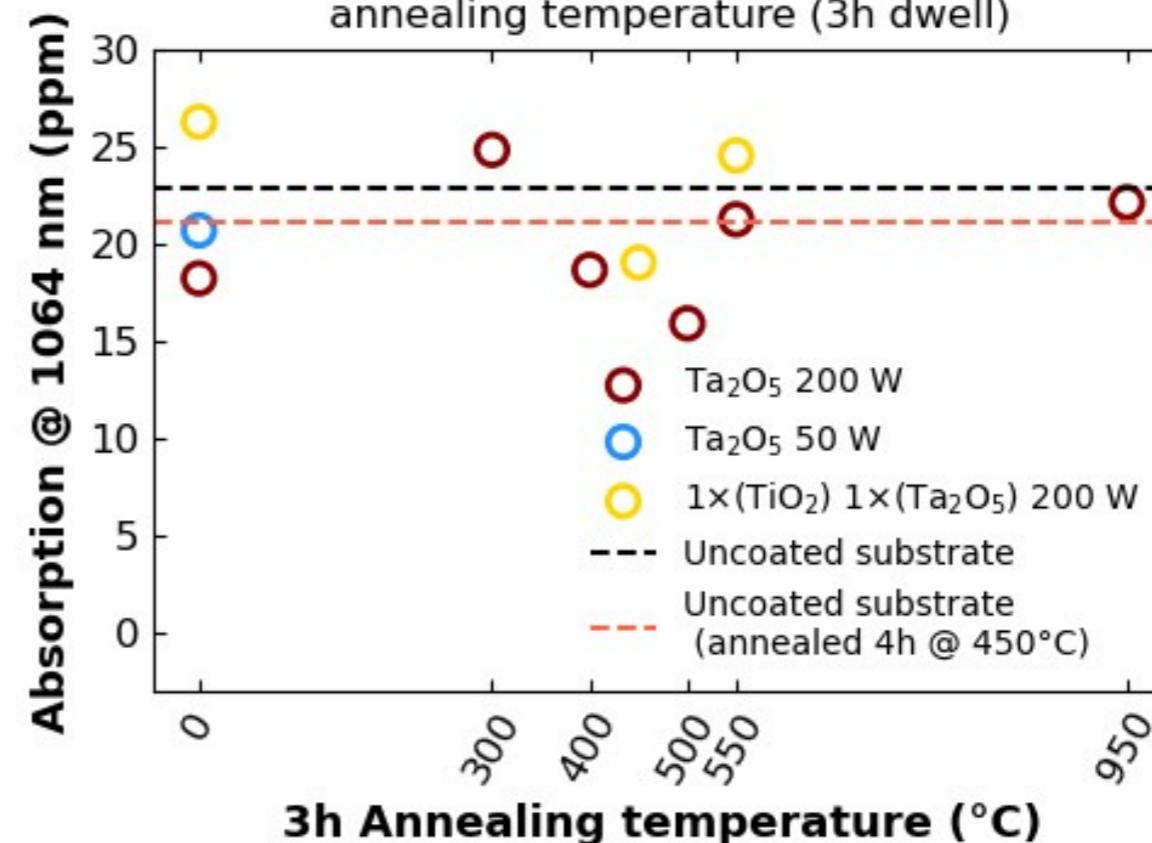
Growth of Ta₂O₅



Influence of coreactant on:

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- Density
- Purity
- **Optical absorption**
- Mechanical losses

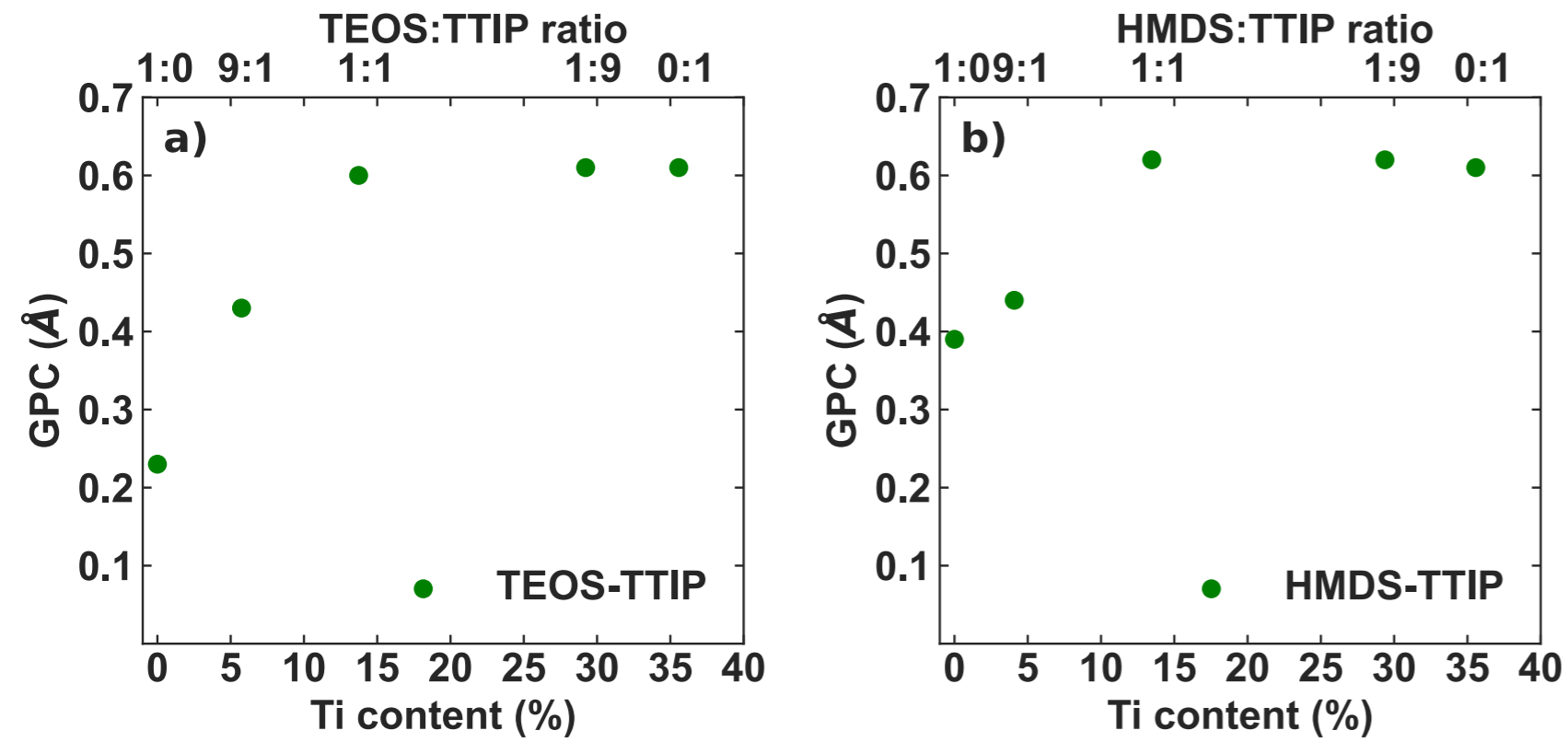
Ta₂O₅ absorption as function of annealing temperature (3h dwell)



Upper boundary for extinction coefficient: 2E-5 (not bad)

Growth of SiO₂

SiO₂ grows faster when TiO₂ is added

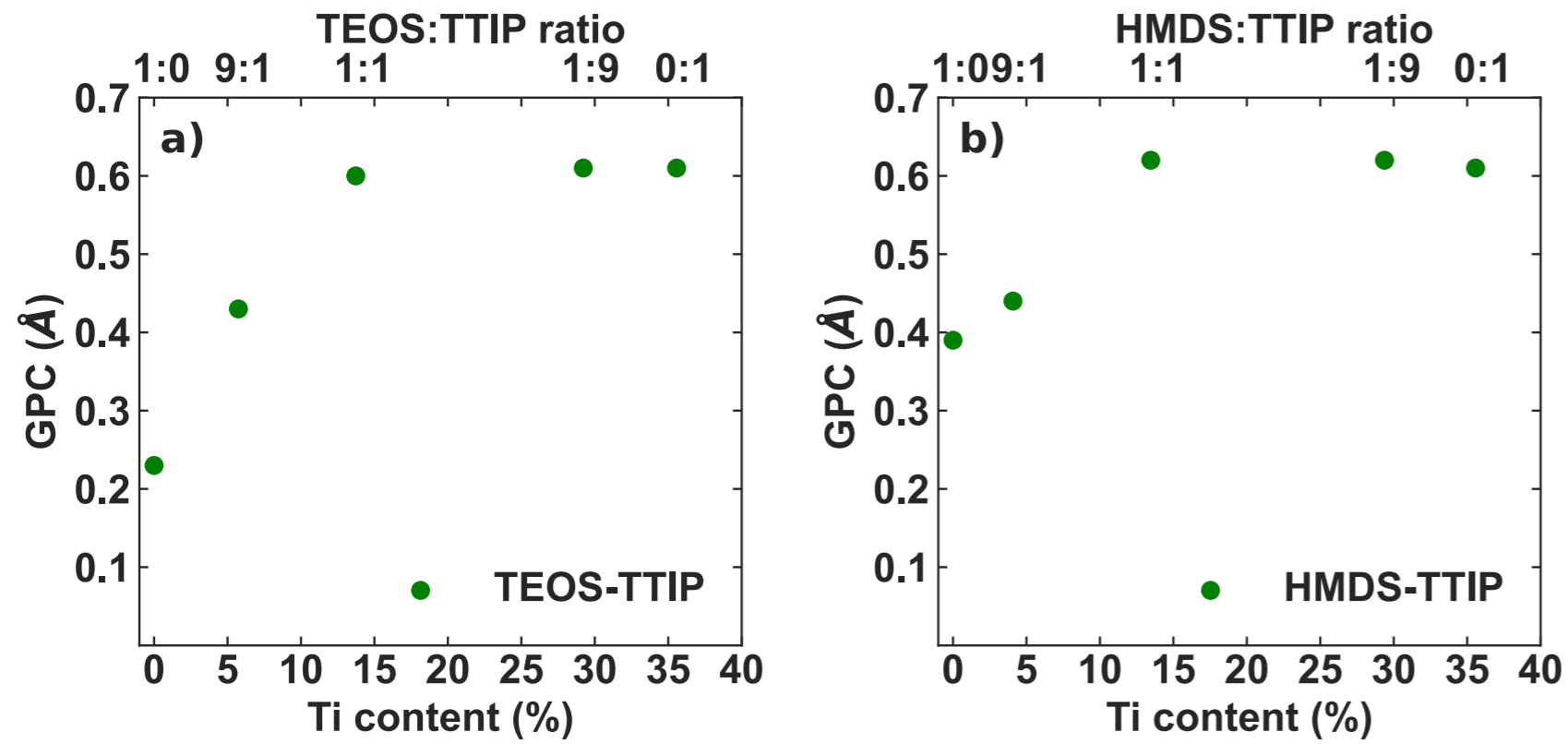


Titania Mixed with Silica: A Low Thermal-Noise Coating Material for Gravitational-Wave Detectors

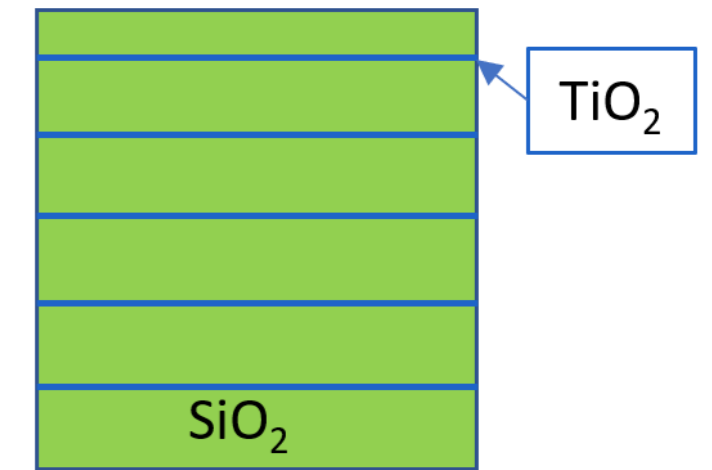
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Growth of SiO₂

SiO₂ grows faster when TiO₂ is added



ALD allows for “delta doping”, where delta layers of the doping material are inserted

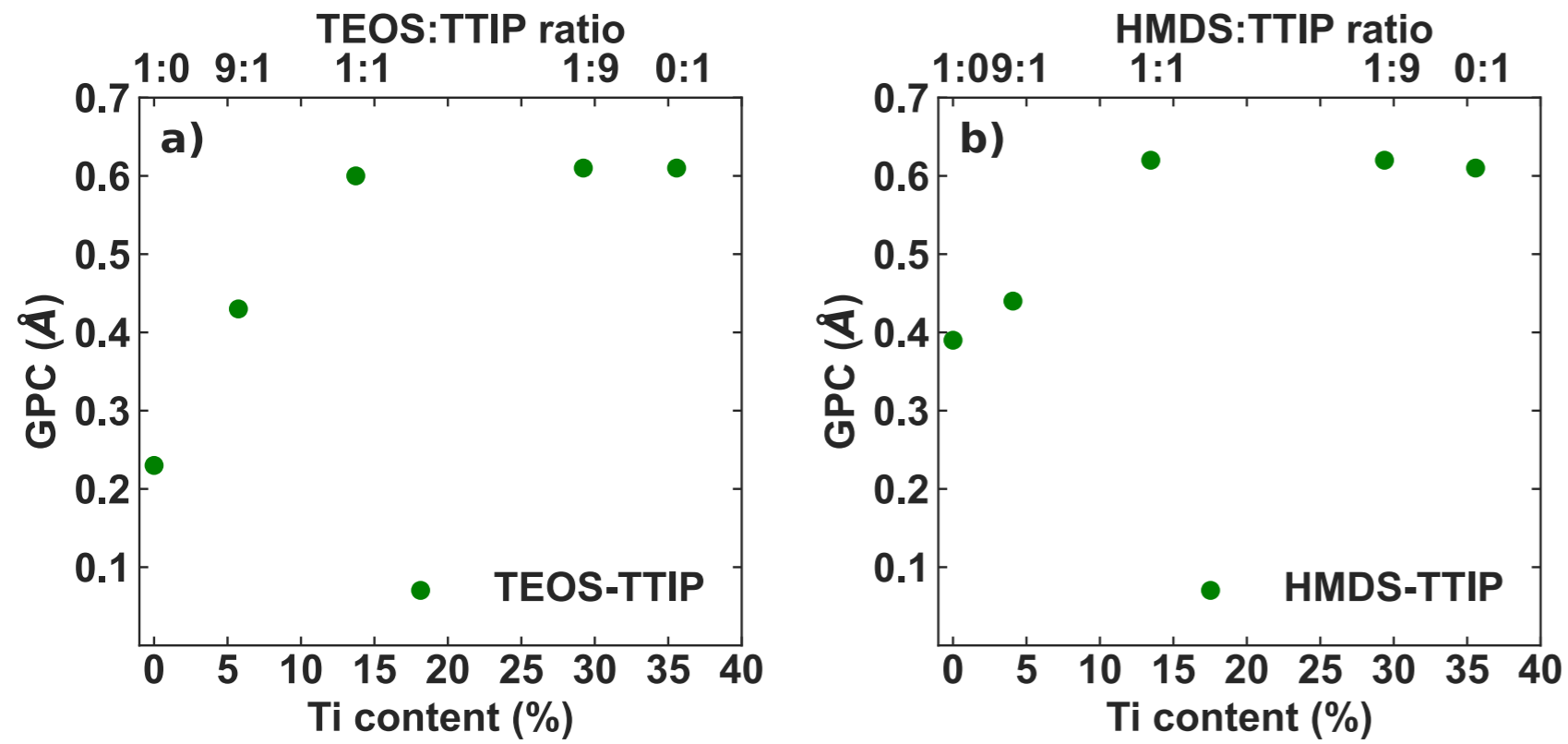


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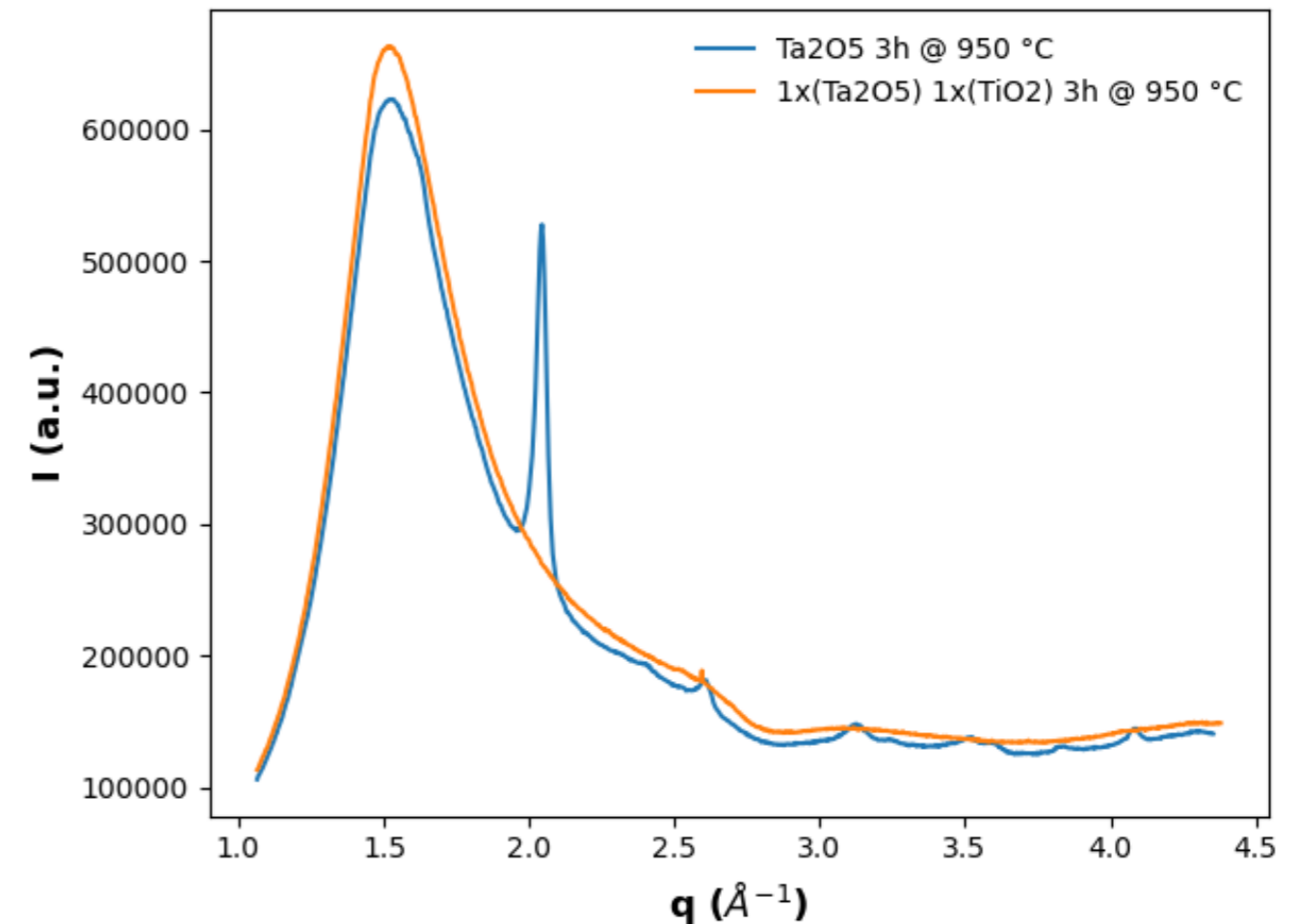
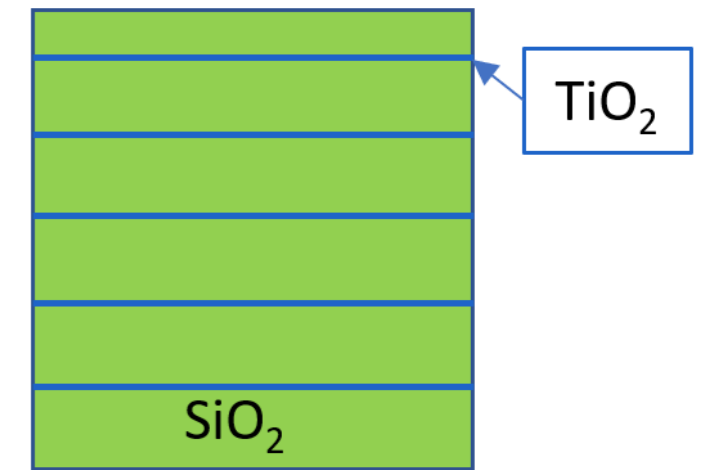
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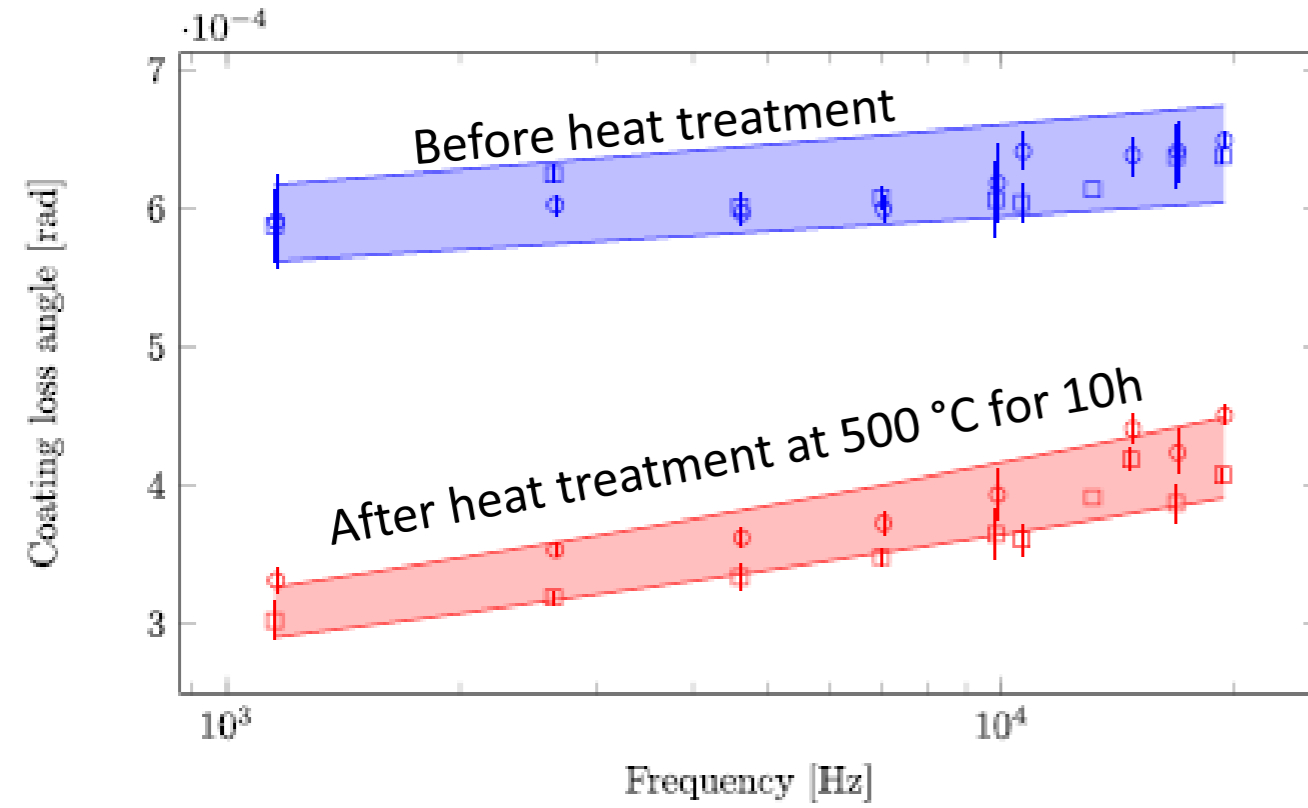
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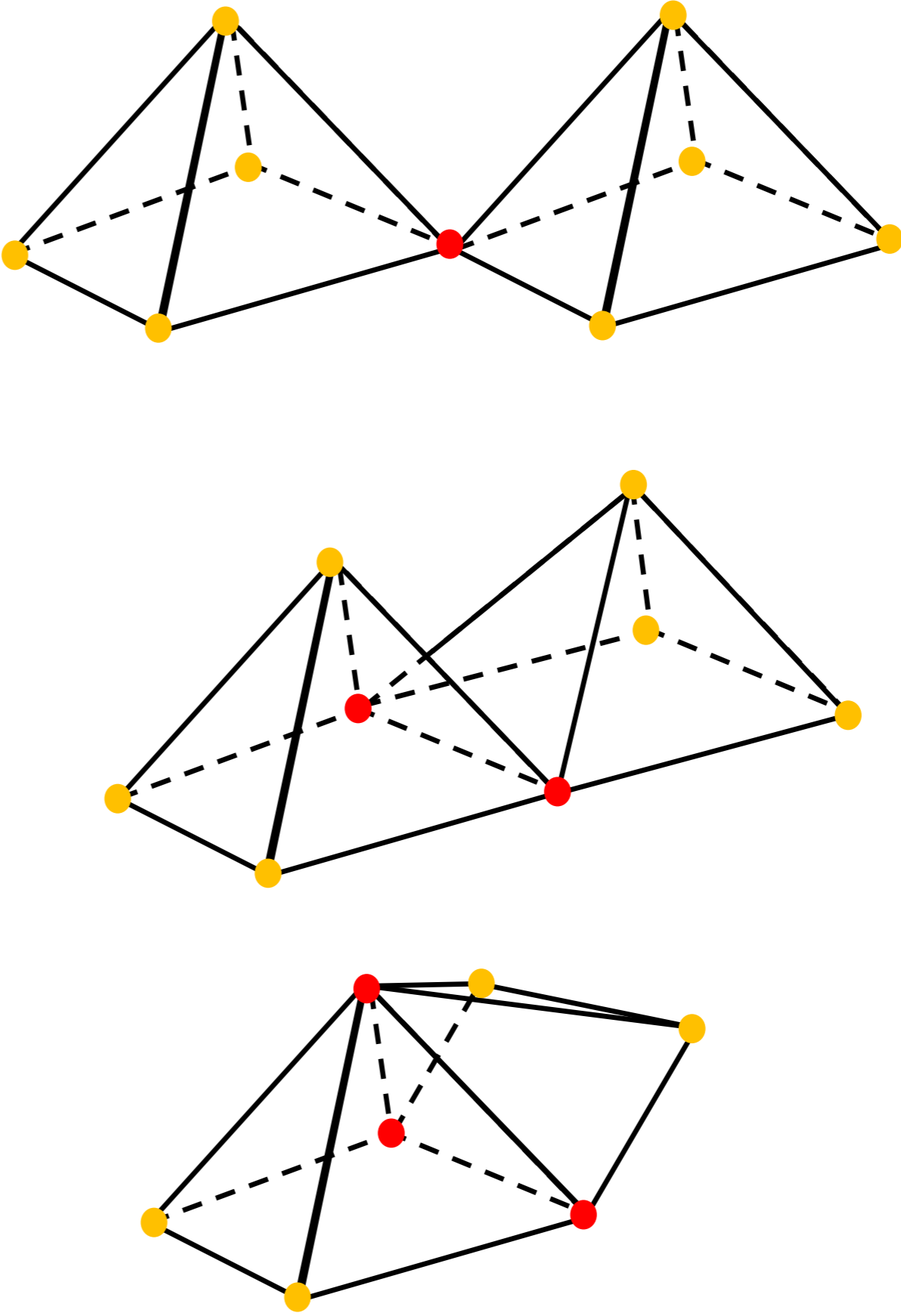
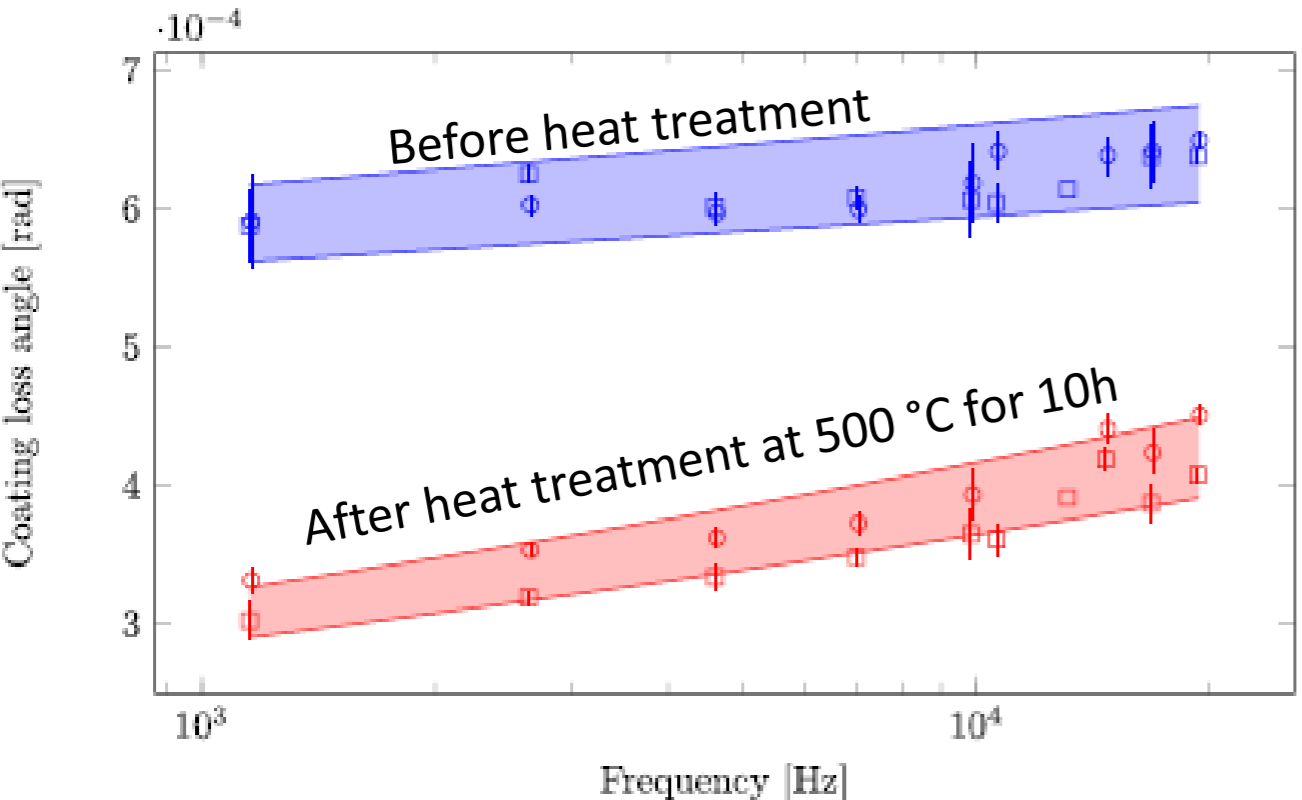


Structural characterisation

Why structure is important



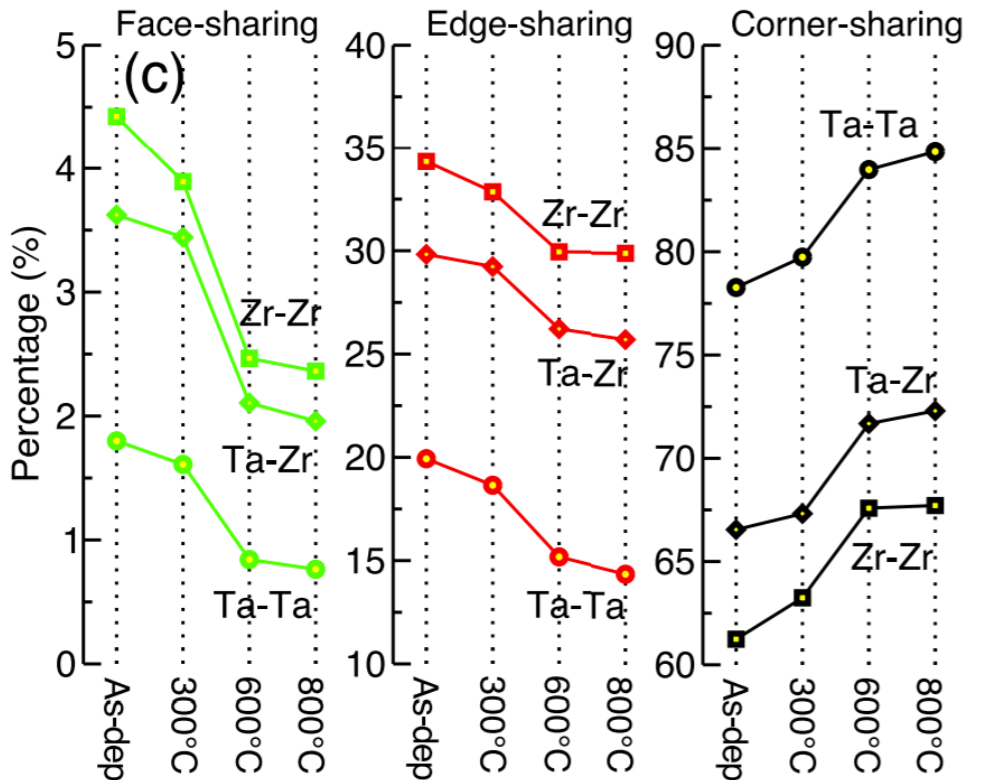
Why structure is important



Corner sharing

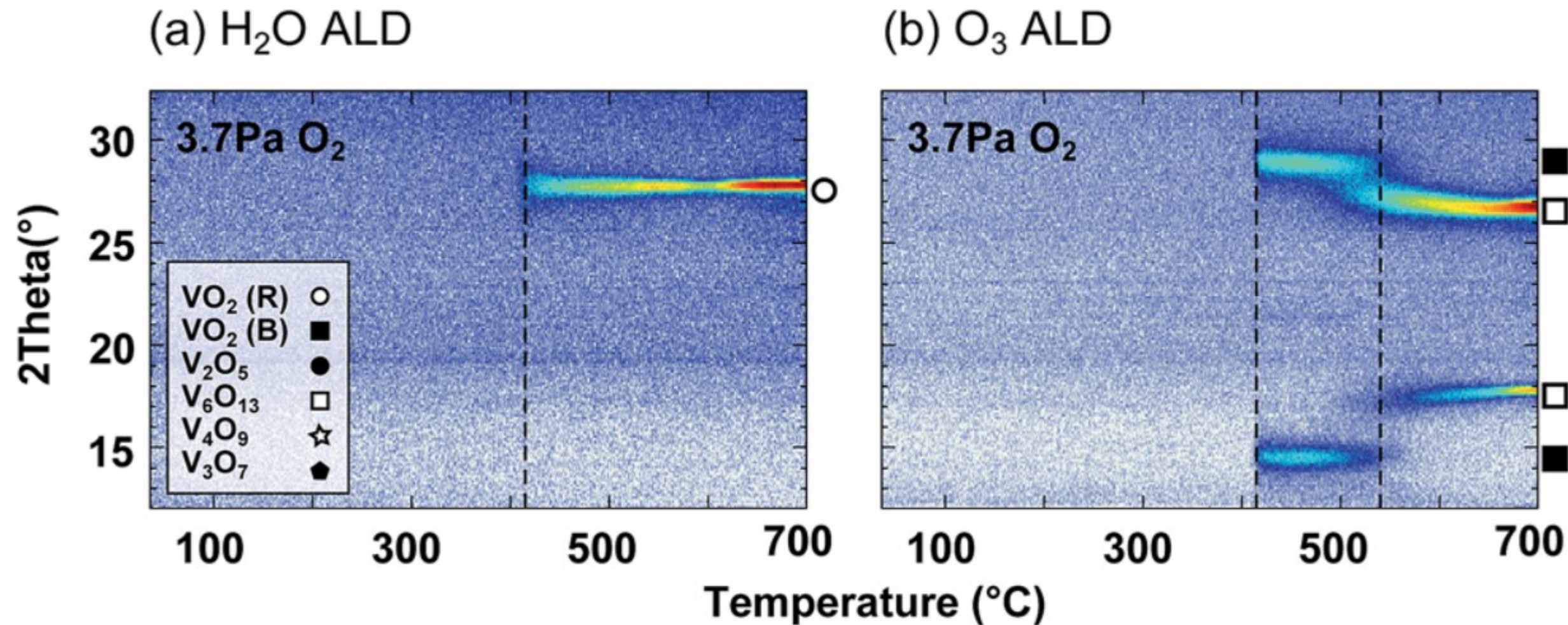
Edge sharing

Face sharing



Why structure is important

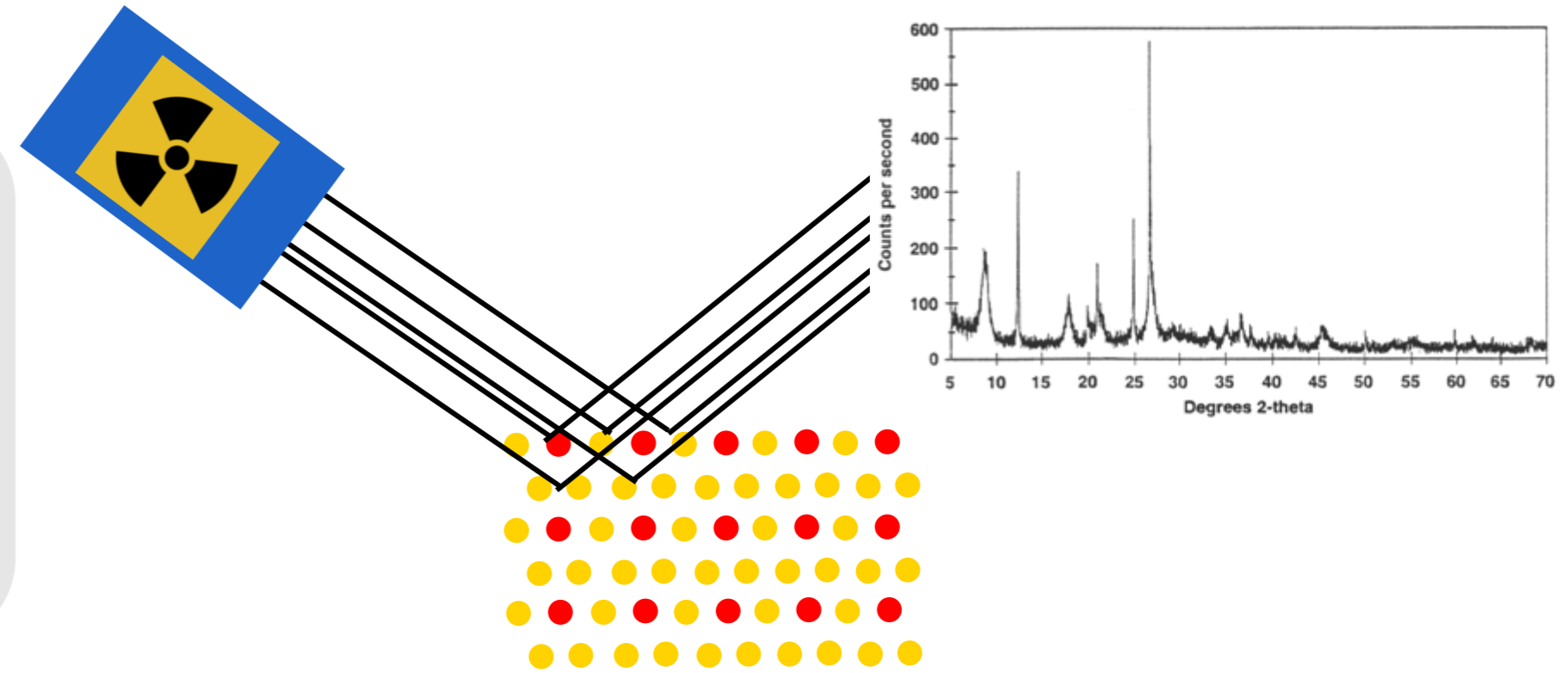
ALD of VO_2 (TEMAV + $\text{H}_2\text{O}/\text{O}_3$)



- Amorphous VO_2 shows different crystallisation behaviour when deposited with different ALD processes
- Hints at differences in amorphous phase

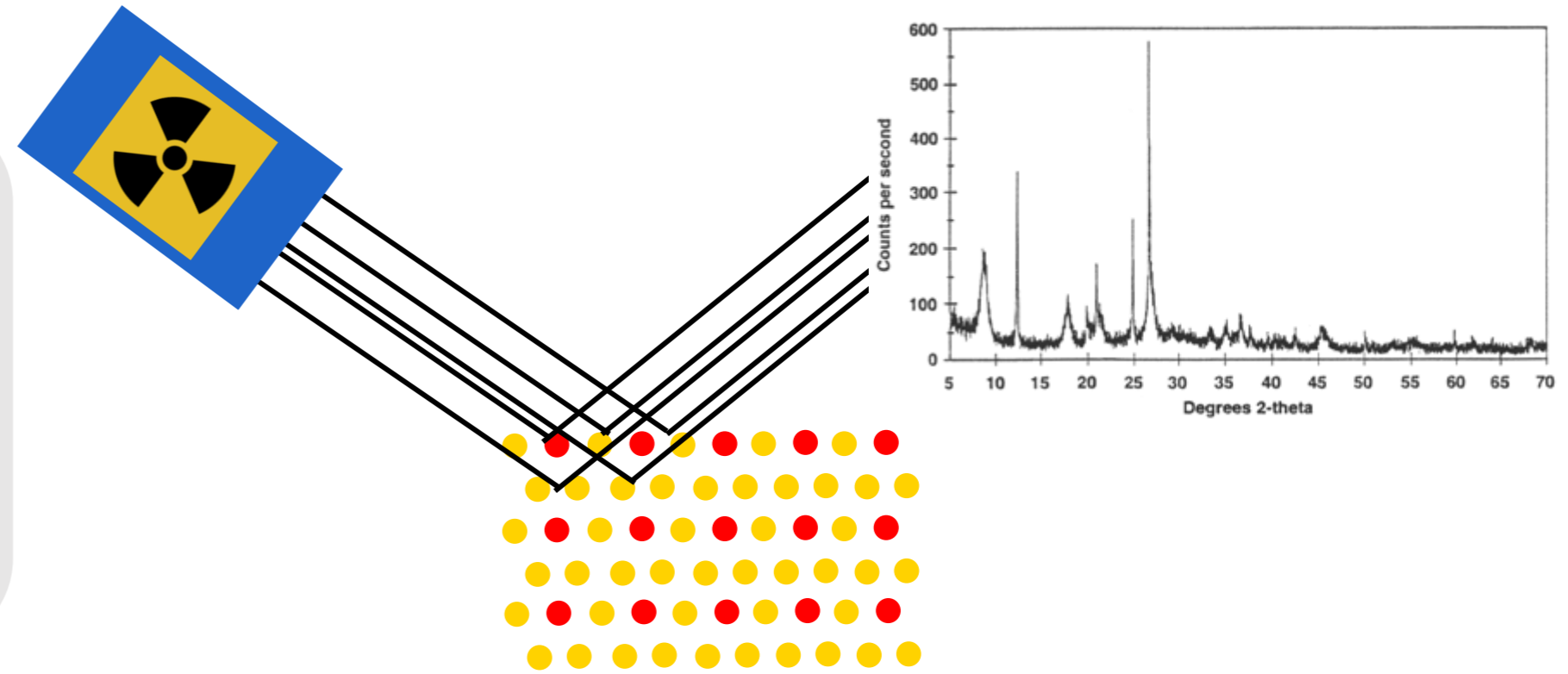
Measuring structure

- For crystalline materials: XRD
 - Measure Bragg scattering
 - Determine lattice parameters very accurately
 - Measures coherence lengths
- Probes the average structure



Measuring structure

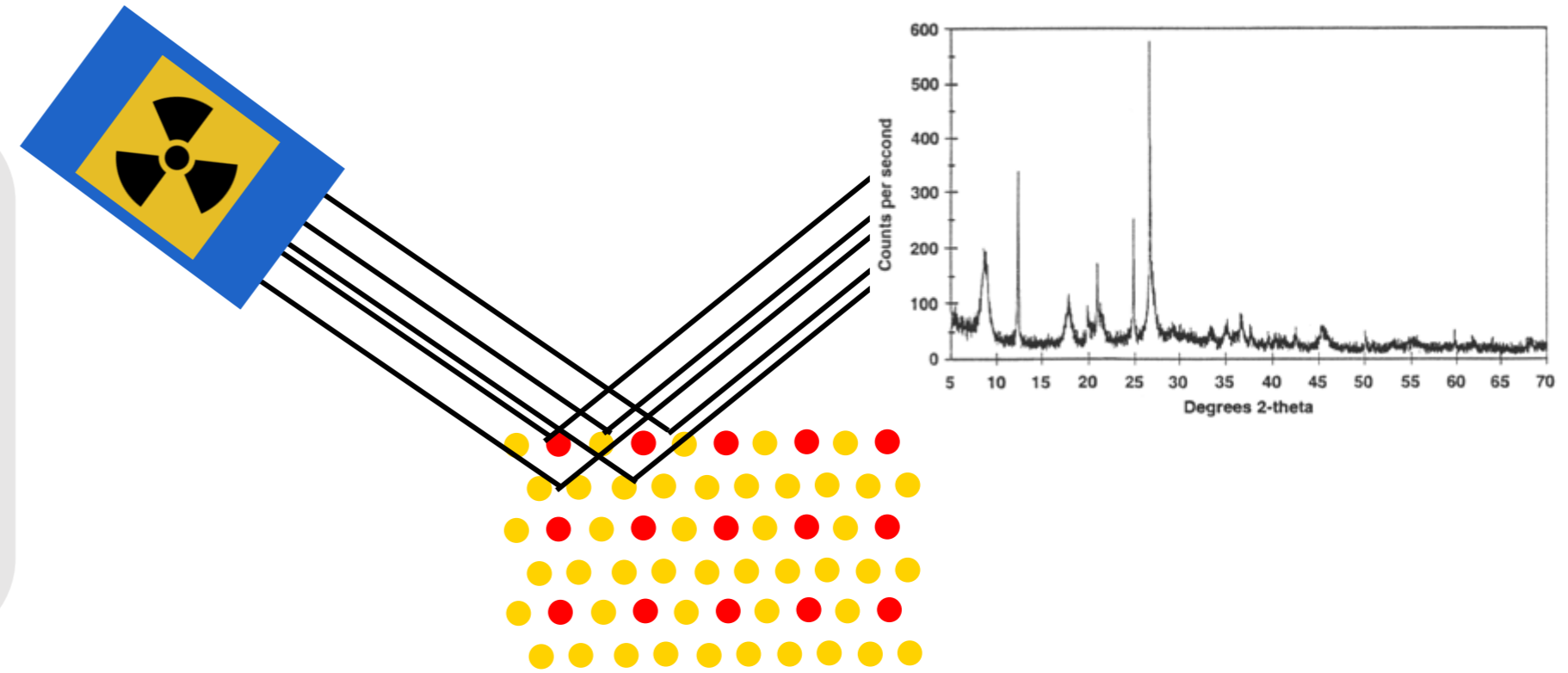
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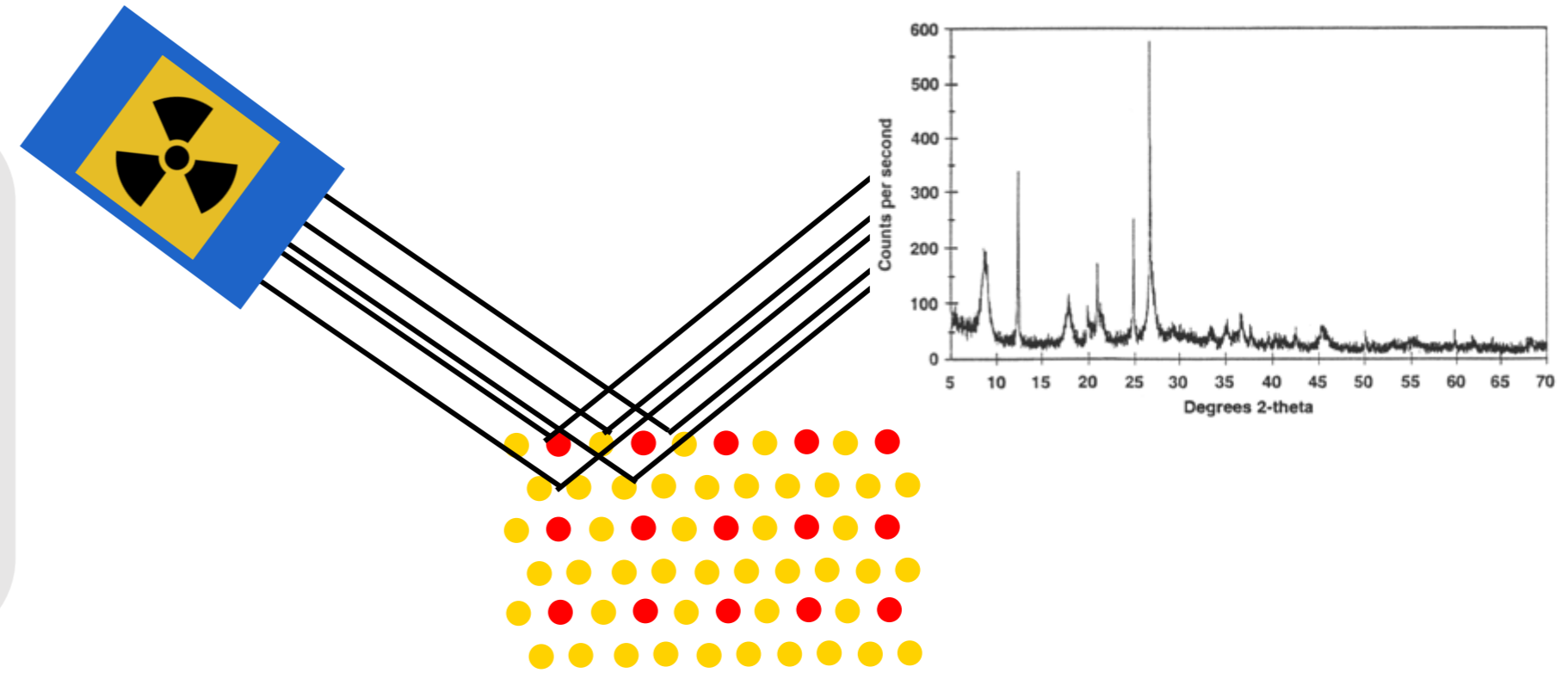
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- For amorphous materials:
 - No long range coherence
- Need to probe local structure



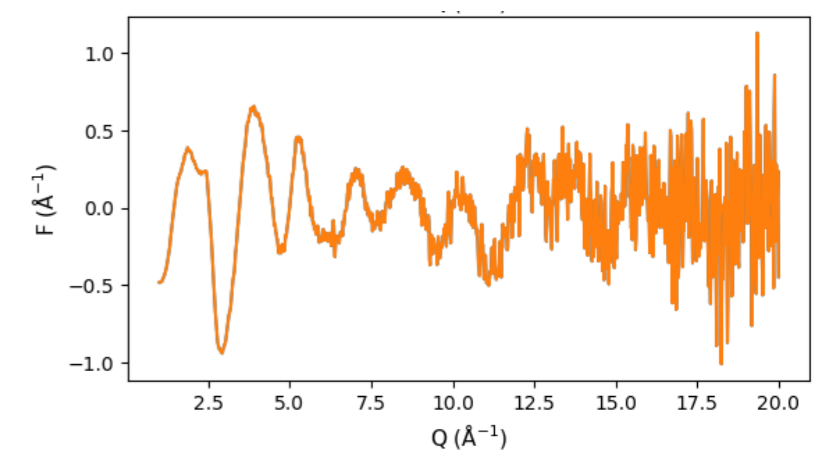
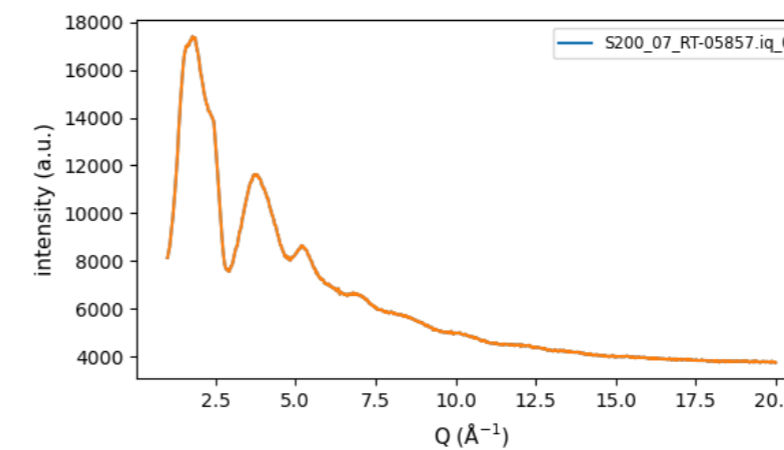
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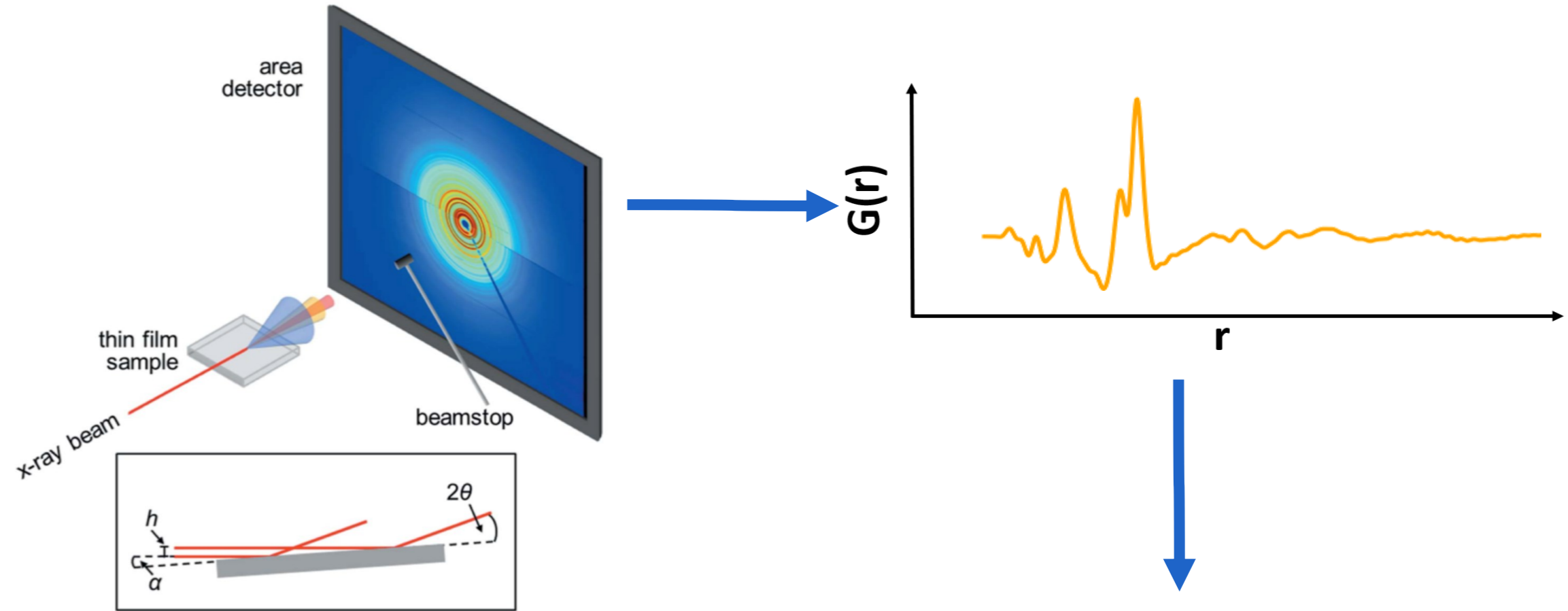
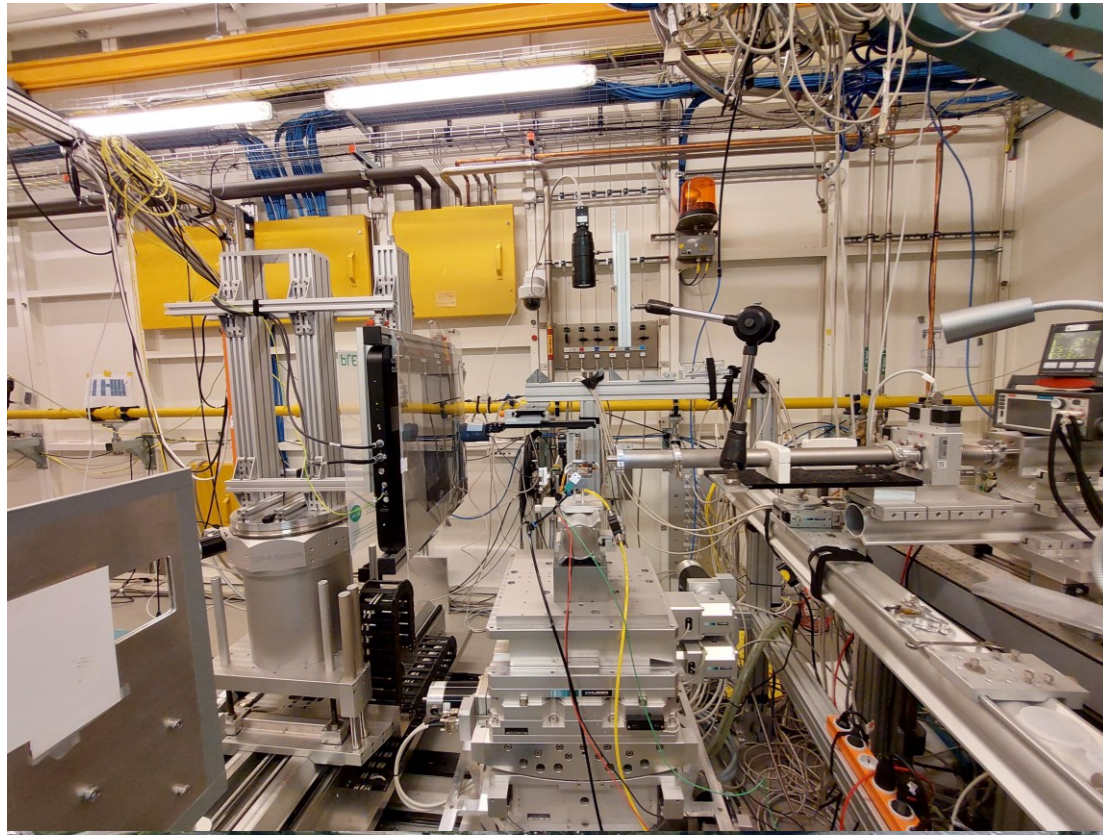


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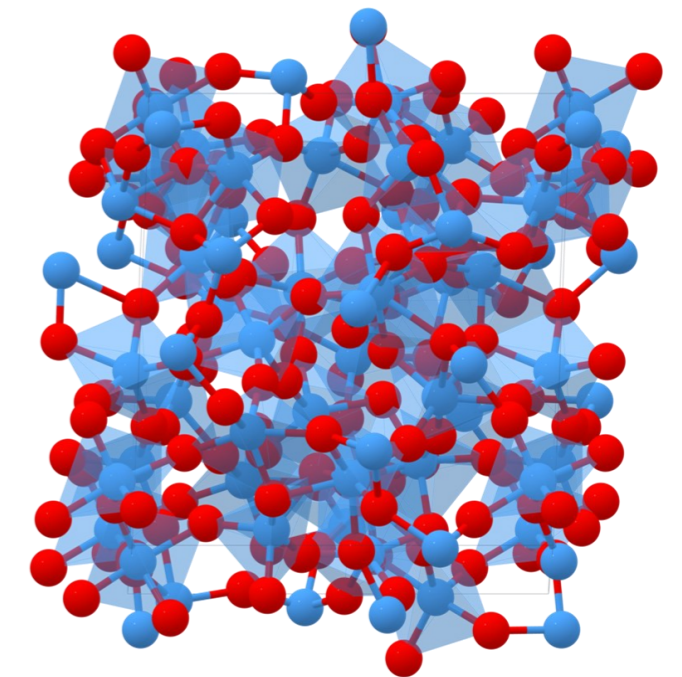
- Measure all scattering (also diffuse scattering)
- Measure high Q-region with good statistics
- Synchrotron based experiments



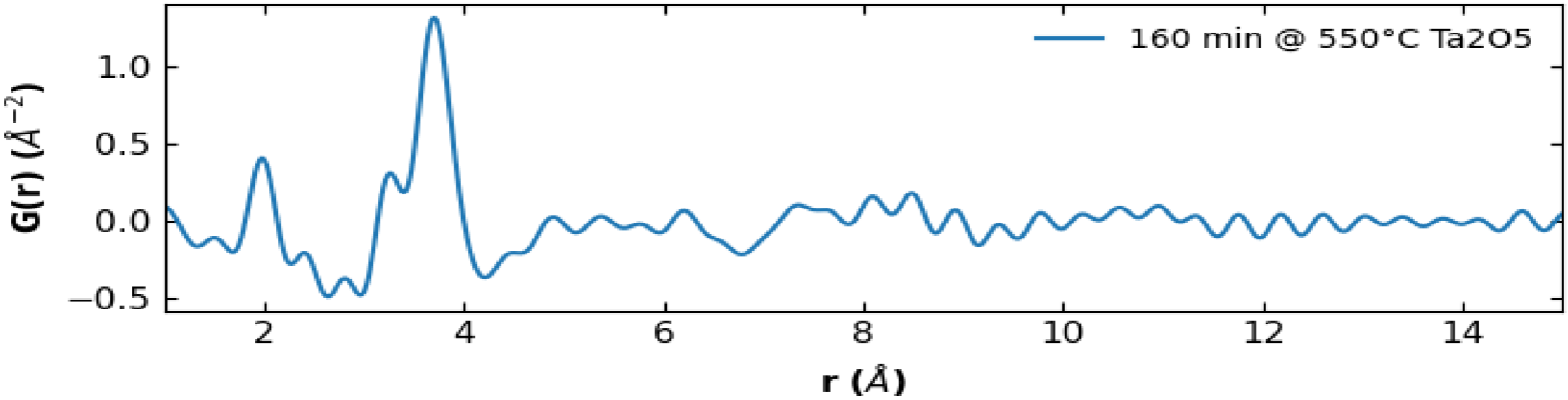
Total scattering experiments



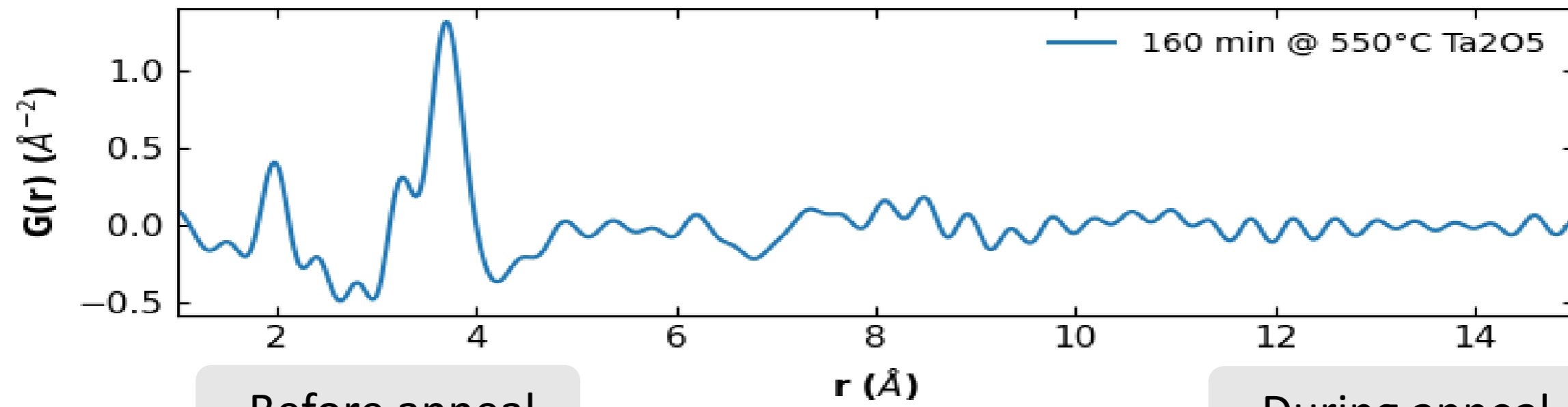
Goal: identifying the fundamental link between deposition conditions, atomic structure and performance of the coatings



PDF of Ta₂O₅

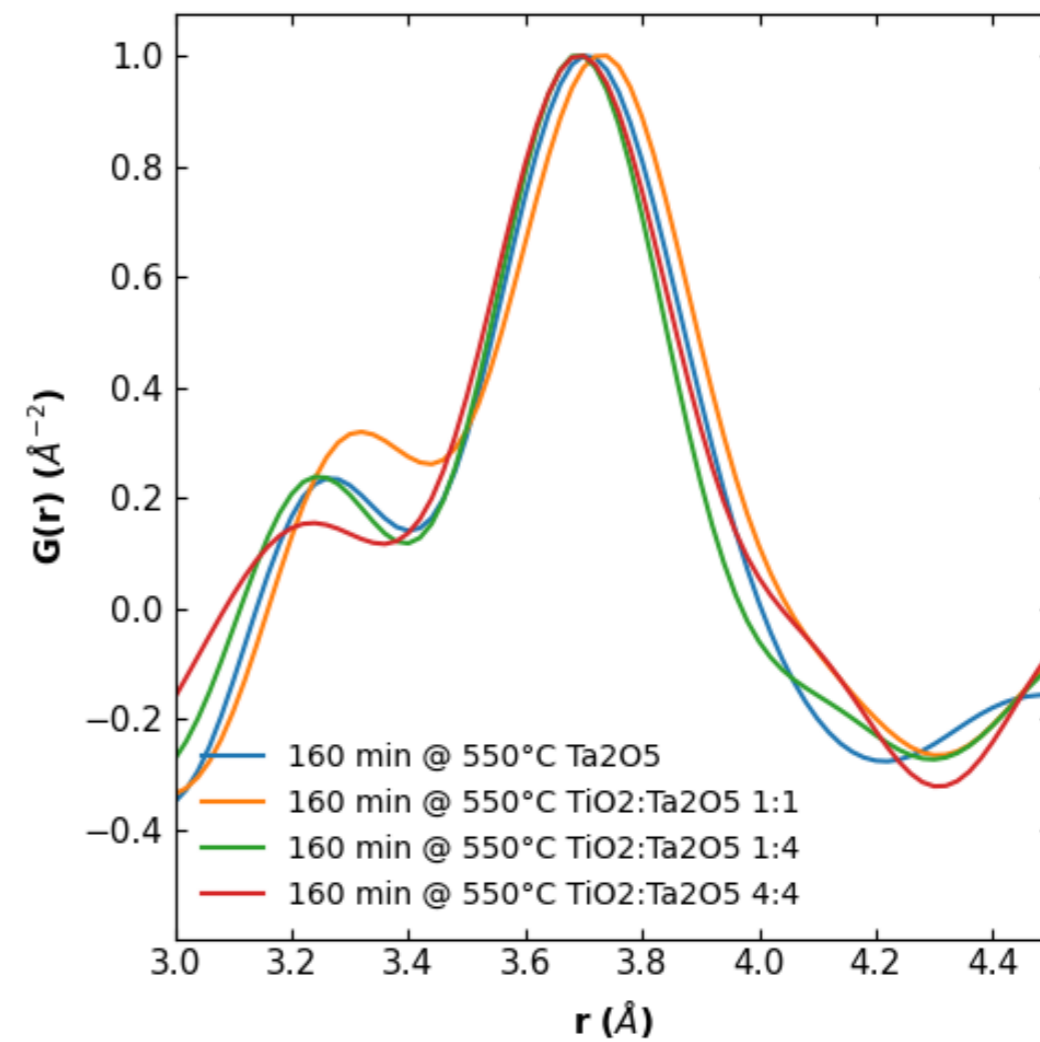
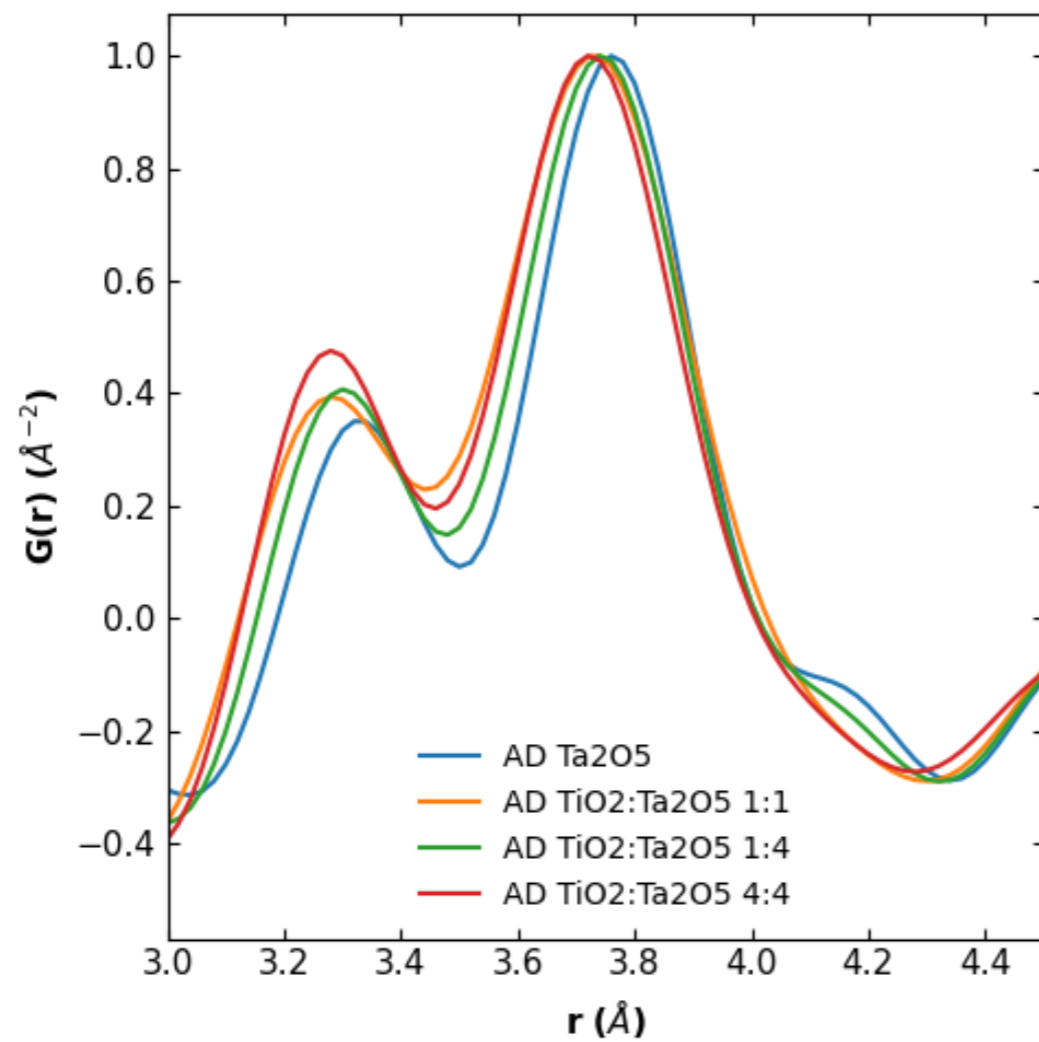


PDF of Ta₂O₅



Before anneal

During anneal



Thank you for your attention

Any questions?

Contact

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